

The Belle II Vertex Pixel Detector

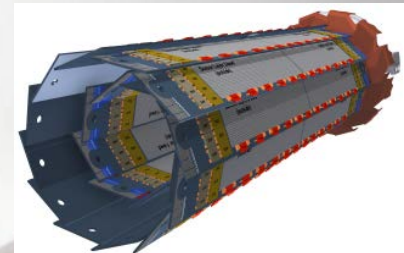
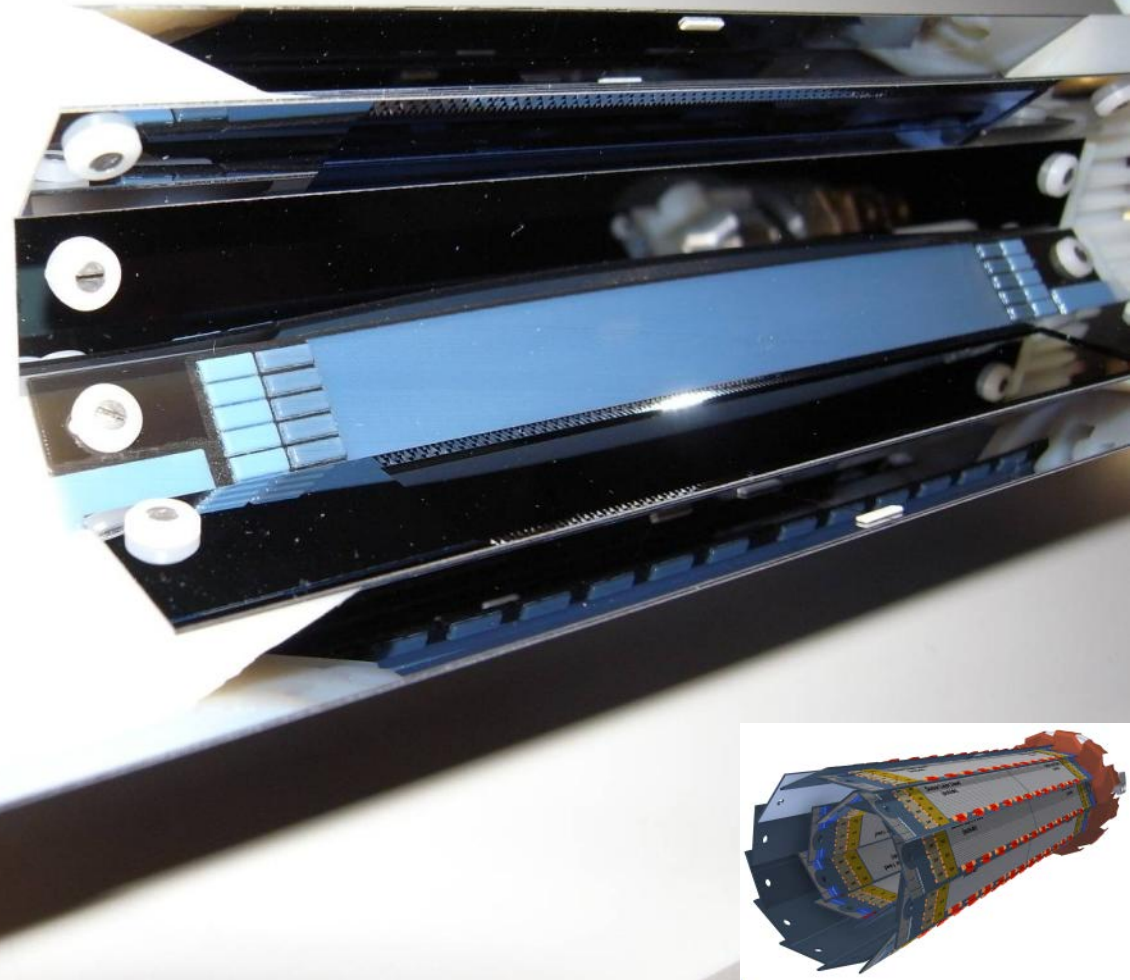


**IMPRS Young
Scientist Workshop**

July 16 - 19, 2014
Ringberg Castle
Kreuth, Germany

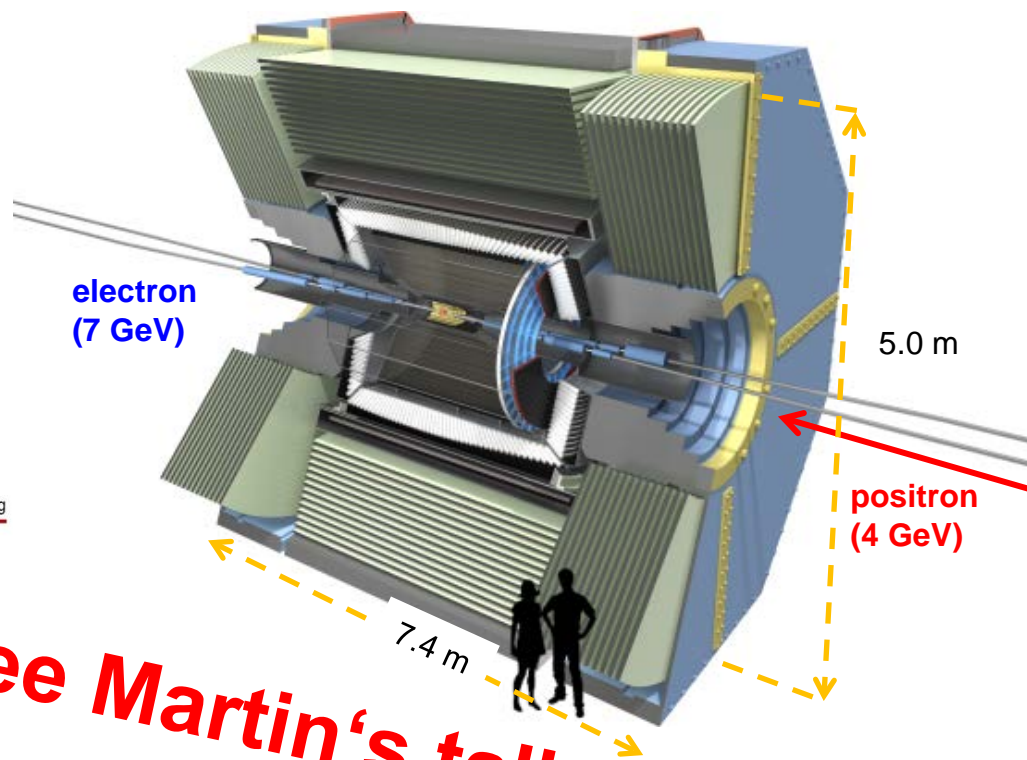
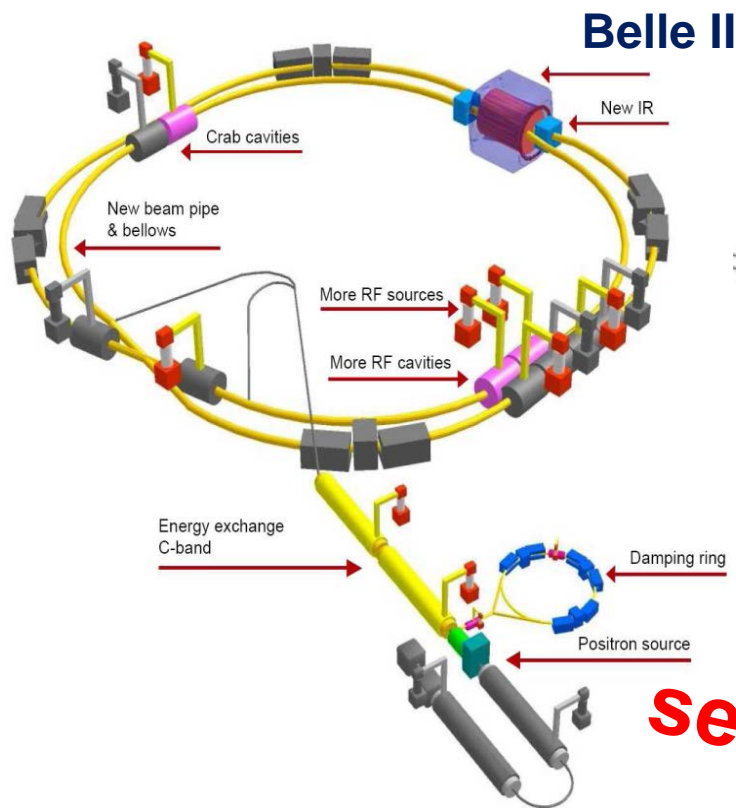


Felix Mueller



- SuperKEKB and Belle II
- Vertex Detector (VXD)
- Pixel Detector (PXD) and its characteristics
- DEPFET technology and working principle
- The readout electronics
- Gated Mode Operation
- Production / Technology Issues
- Lab Measurements and TestBeam with PXD6
- Summary and future plans

SuperKEKB upgrade



see Martin's talk

Nano beam scheme → smaller beam size (~nm)
& increased beam currents (x2)

- $\mathcal{L} = 8 \times 10^{35} \text{ cm}^{-2} \text{ s}^{-1}$ (40 times larger than in KEKB)
- $E_{e^-} = 7$ (8) GeV & $E_{e^+} = 4$ (3.5) GeV
($\beta\gamma = 0.42$ (KEK) → **0.28** (SuperKEK))
- $E_{\text{cm}} = 10.58 \text{ GeV} - Y(4S)$

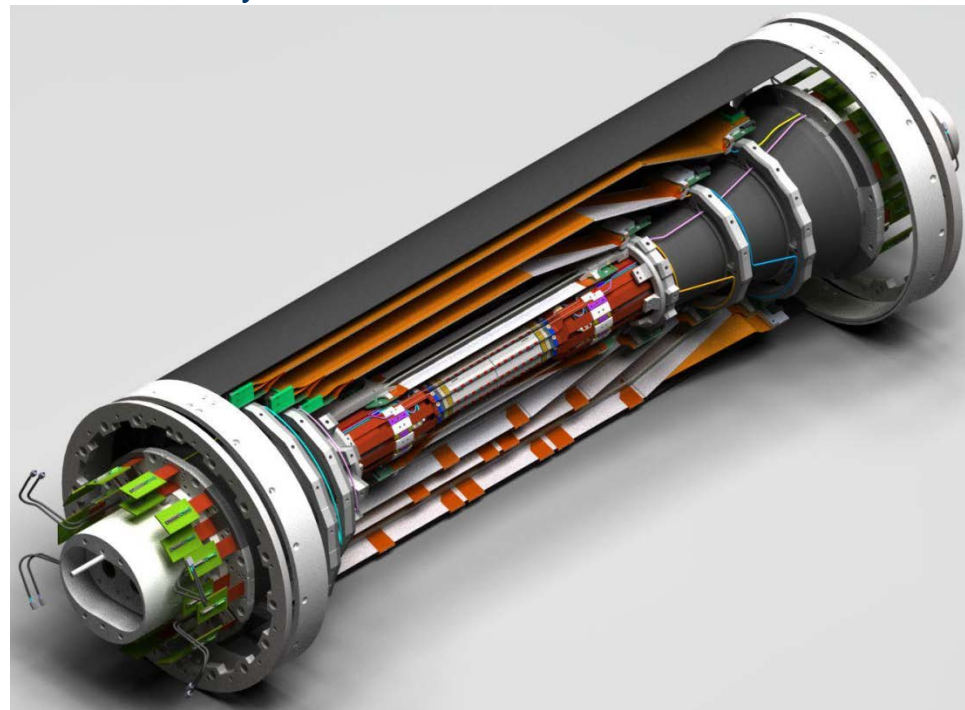
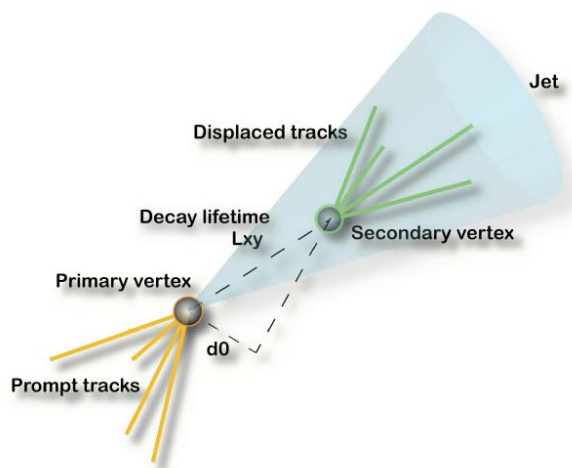
Changes involving the Vertex Detector (VXD):

- Four layers of Double Sided Si-Strip Detector (DSSD) with a larger radius
- Two layers of DEPFET pixel detector (PXD)

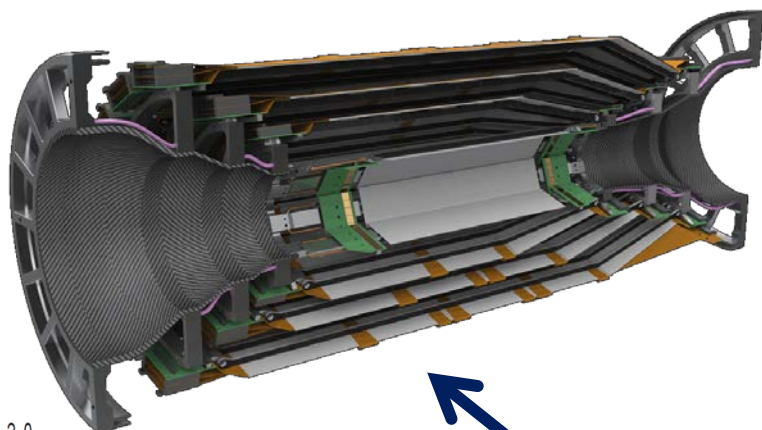
Vertex Detector (VXD)

Tasks of the vertex detector:

- reconstruction of primary, secondary, ... vertices of short-lived particles
decay of particles is typical in the order of 100 μm from the IP
- detect tracks of low momentum particles (in high B field) which cannot make it to the main tracker
 - Innermost detector system as close as possible to IP
 - highly granular pixel sensors; provide most accurate 2D position information
 - should be massless and still provide a large enough S/N
 - Design and specifications to a larger extent driven by machine/beam characteristics
 - Beam background, radiation damage, occupancy ...



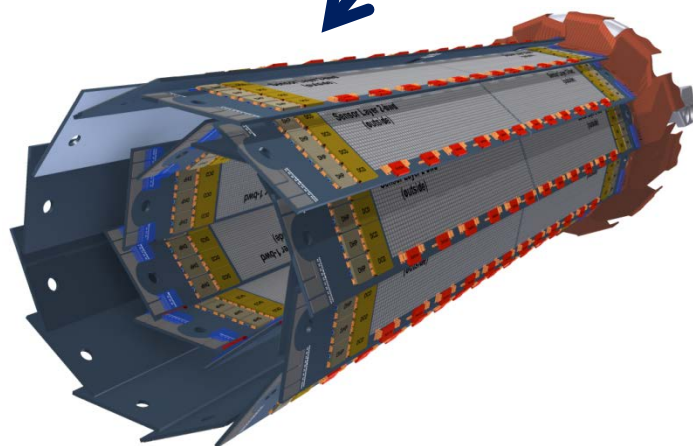
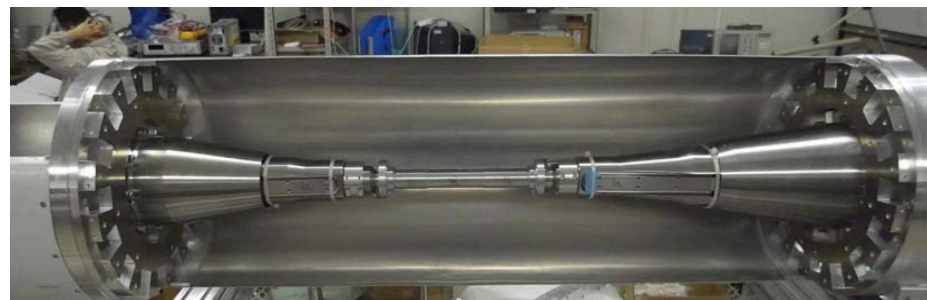
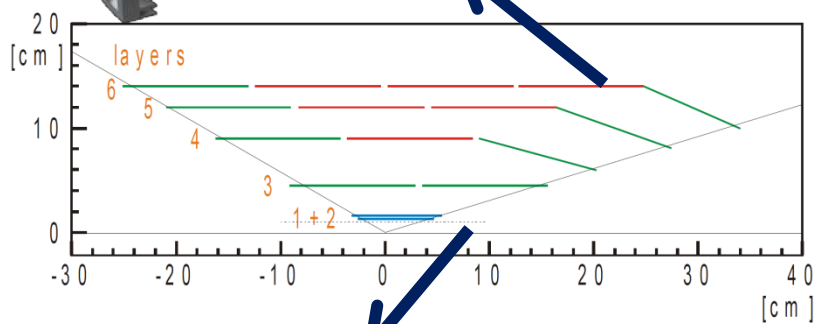
Vertex Detector (VXD)



Silicon Vertex Detector (SVD)

4 layers of double sided silicon strip detector

$R = 3.8 \text{ cm}, 8.0 \text{ cm}, 11.5 \text{ cm}, 14 \text{ cm}$

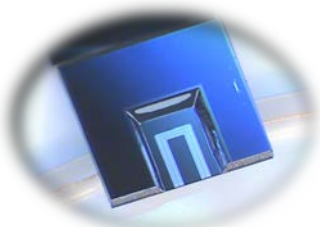


Pixel Detector (PXD)

2 layers of DEPFET pixels

$R = 1.4 \text{ cm}, 2.2 \text{ cm}$

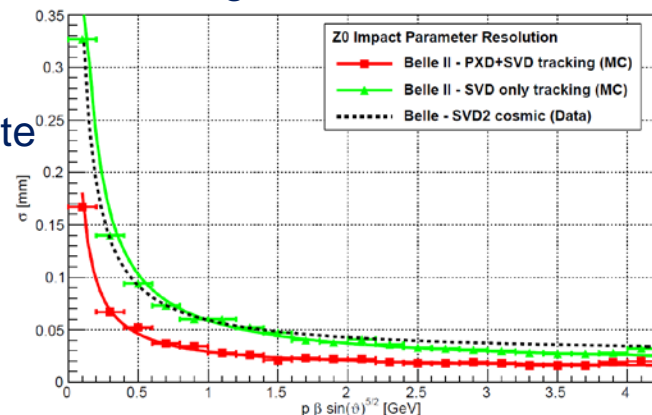
PXD detector requirements



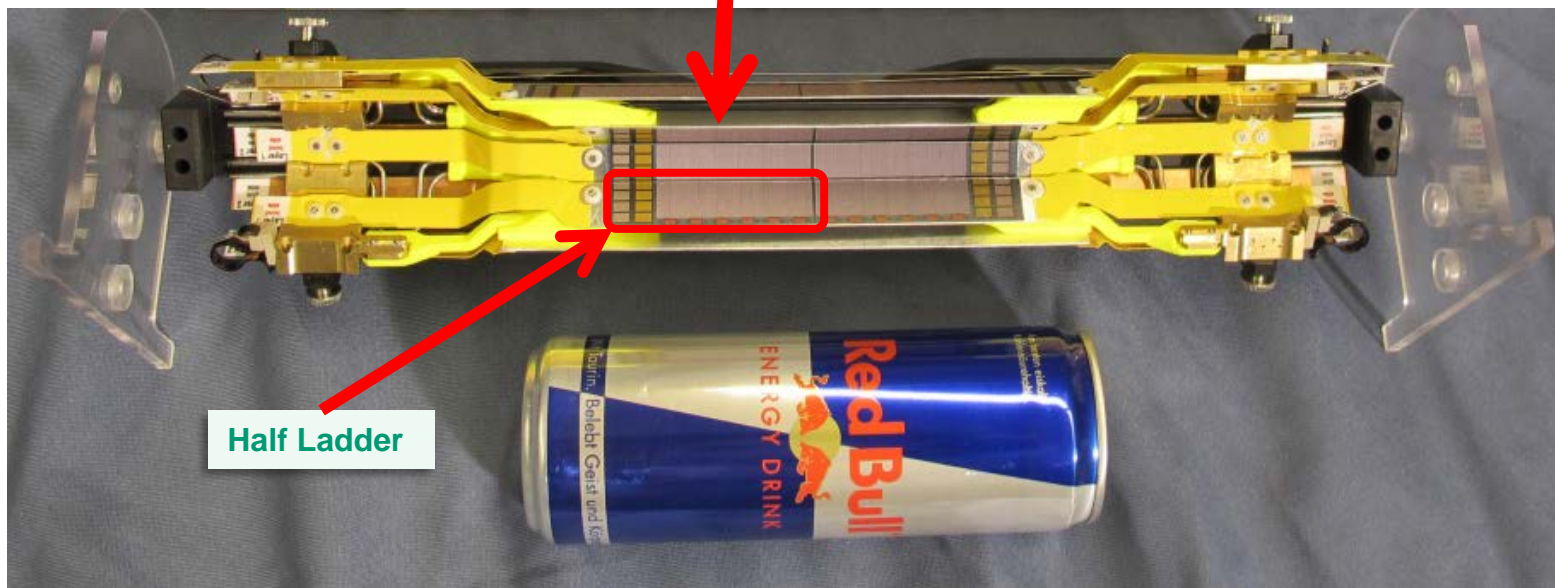
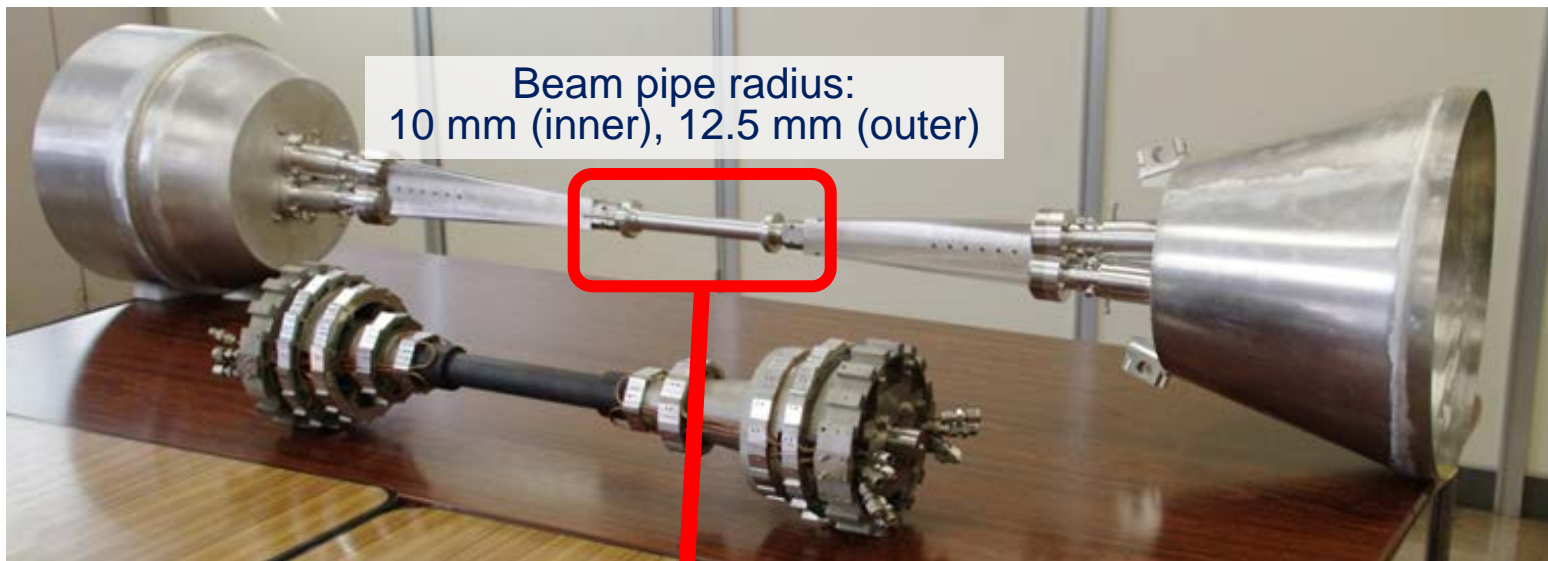
| | |
|----------------|--|
| Occupancy | 0.1 hits/ $\mu\text{m}^2/\text{s}$ |
| Frame time | 20 μs (rolling shutter mode) |
| Momentum range | Low momentum (<1GeV) |
| Acceptance | 17°-150° |
| Radiation | ~20 kGy/year, $1 \cdot 10^{10}$ n/ab ⁻¹ cm ² |



- Belle II is dominated by low momentum tracks
- Modest intrinsic resolution (15 μm), dominated by multiple scattering → Moderate pixel size (50 x 75 μm^2)
- Lowest possible material budget (0.2% X_0/layer) [including ASICs]
- due to higher background (20x-40x): Radiation damage and occupancy, fake hits and pile-up noise
- 10x higher event rate => higher trigger rate
- Replace inner layers of SVD with PXD

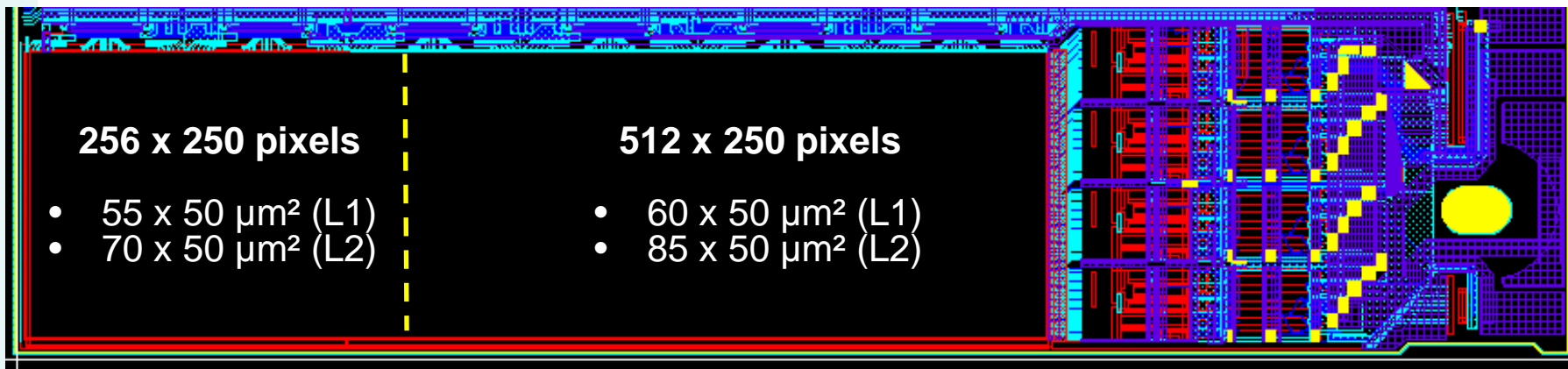
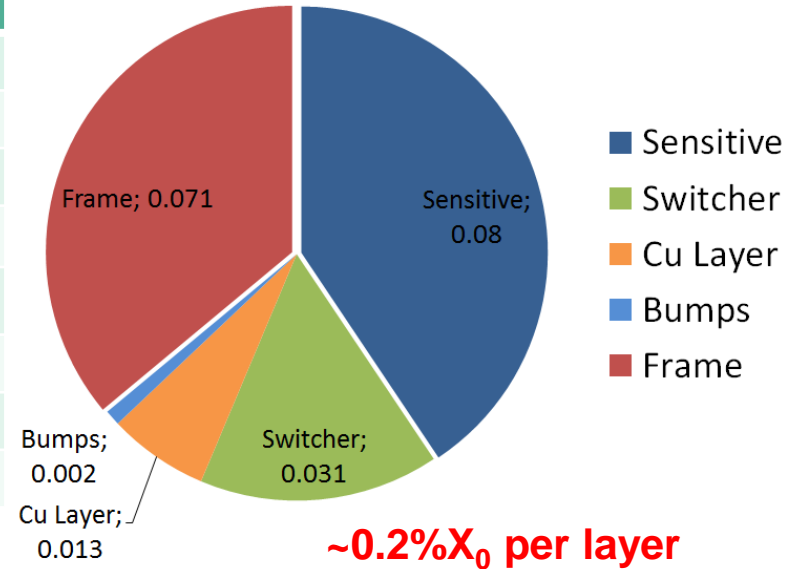


Mockup of the Belle II PXD Detector



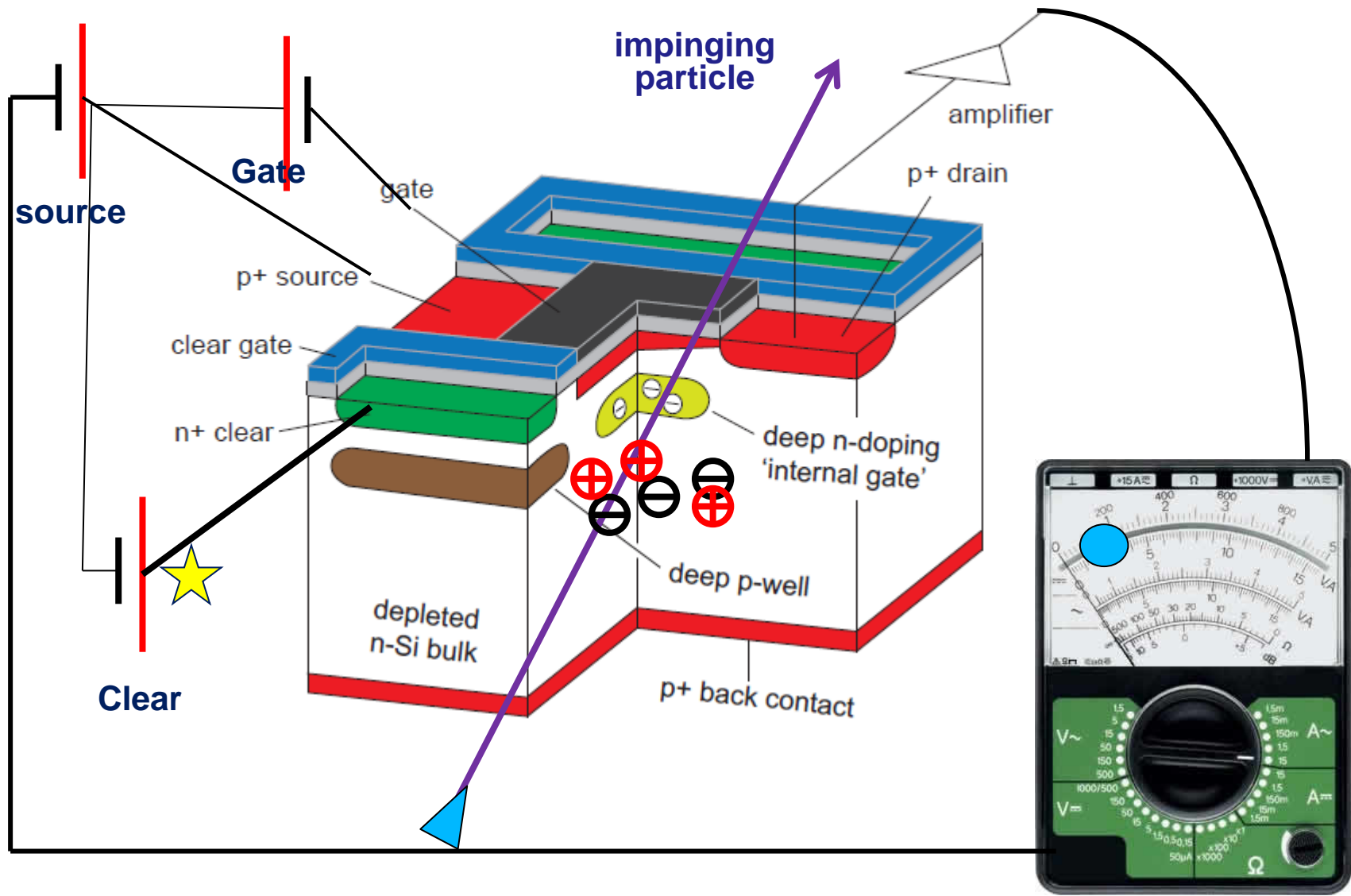
Half Ladder of DEPFET PXD

| | Inner layer (L1) | Outer layer (L2) |
|----------------------------------|---------------------|---------------------|
| # modules | 8 | 12 |
| Distance from IP (cm) | 1.4 | 2.2 |
| Thickness (μm) | 75 | 75 |
| Total # pixels | 3.072×10^6 | 4.608×10^6 |
| Pixel size (μm^2) | 55, 60 x 50 | 70, 85 x 50 |
| Sensitive area (mm^2) | 44.8 x 12.5 | 61.44 x 12.5 |
| Sensor length (mm) | 90 | 123 |
| Frame/Row rate | 50 kHz / 10 MHz | 50 kHz / 10 MHz |



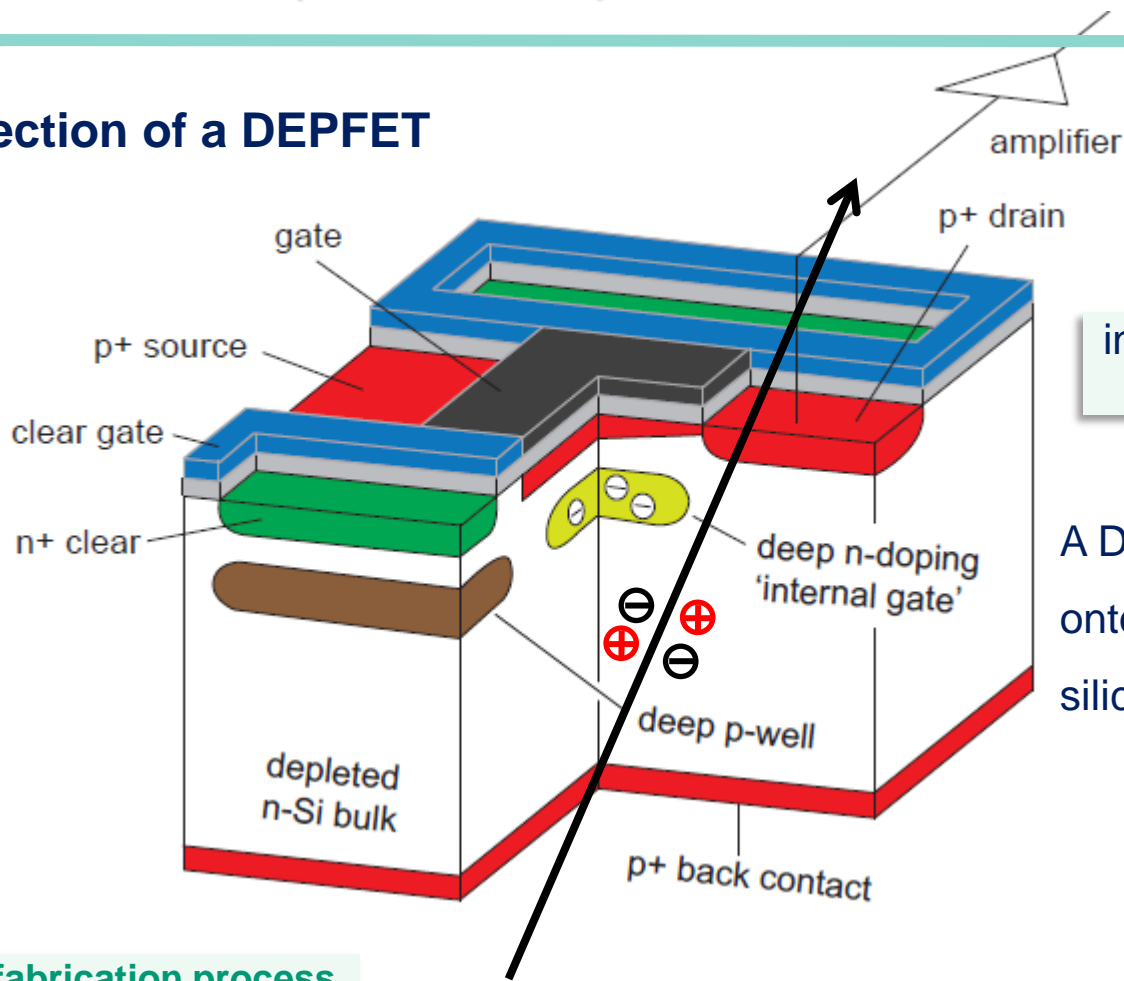
DEPFET (DEPLEted p-channel Field Effect Transistor)

Turn on DEPFET



DEPFET (DEPLEted p-channel Field Effect Transistor)

Cross-section of a DEPFET



internal amplification:
 $g_q \approx 0.5 \text{ nA/e}^-$

A DEPFET is a MOSFET onto a sideward depleted silicon bulk

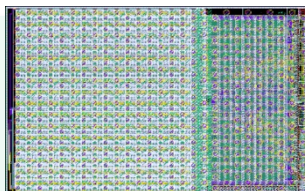
- 90 steps fabrication process**
- 9 Implantations
 - 19 Lithographies
 - 2 Polysilicon layers
 - 2 Aluminum layers
 - 1 Copper layer
 - Back side processing

- Low noise
- Low power
- High signal/noise-ratio
- Non-destructive readout

Control and readout electronics

Drain Current Digitizer (DCD)

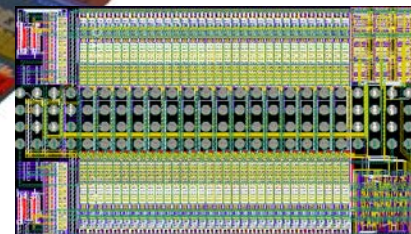
- Keeps the columns line potential constant
- 8 bit ADCs
- Compensates for pedestal current variation (2bit DAC)
- Programmable gain and BW
- 256 input channels (4 per module)



DEPFET

SWITCHER

- Fast voltage pulses up to 20 V to activate gate rows and to clear the internal gate
- JTAG for interconnectivity tests
- 64 output drivers for both gate and clear channels → address 32 matrix segments
- 768 rows → 192 electrical rows → 6 ASICs needed per module

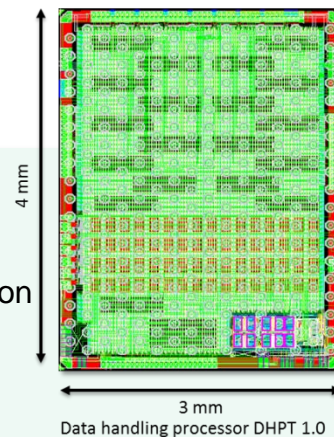


Data Handling Processor (DHP)

- Pedestal correction
- Common mode correction
- Data reduction using the zero suppression
- Triggered readout scheme introduces further data reduction
- Controls the Switcher sequence

Kapton Flex cable

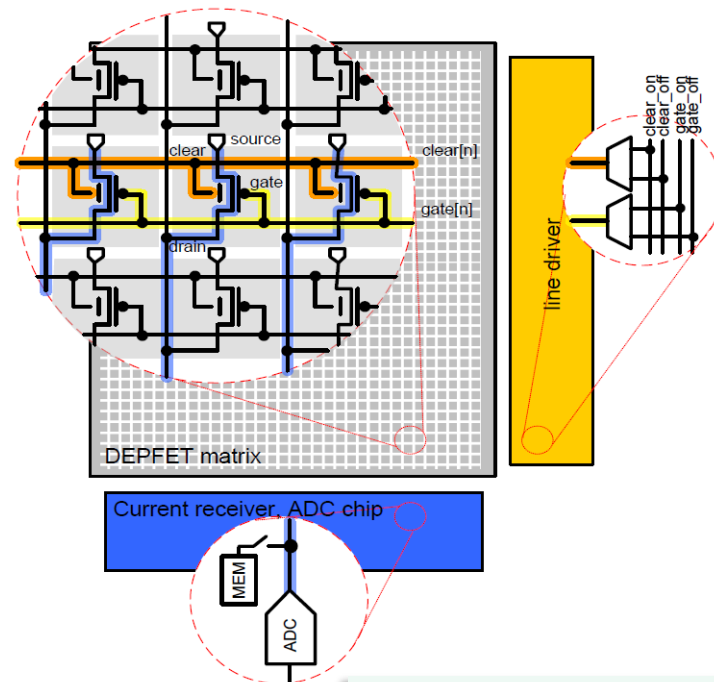
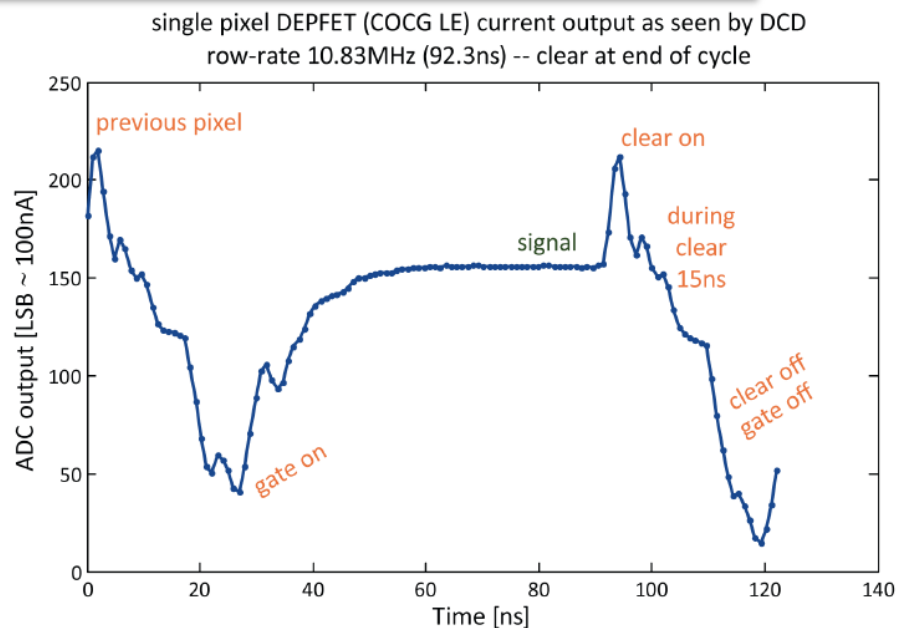
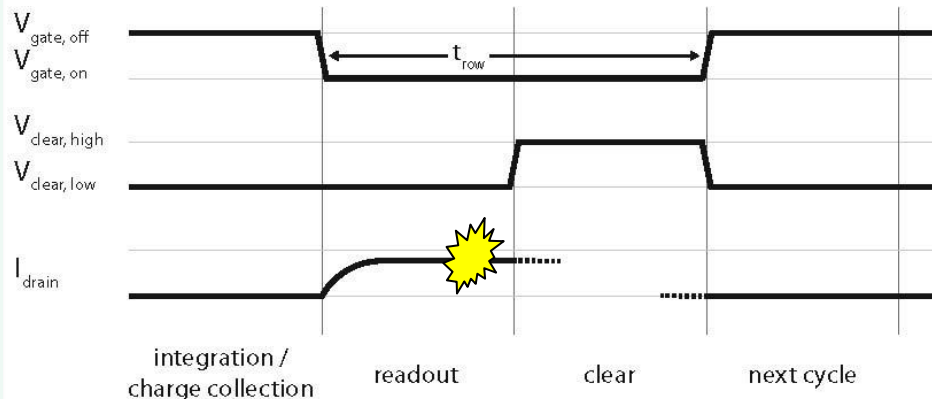
- Power Supply via soldered contacts and bond wires
- Data transmission via bond wires
- 4 layers, 48 cm



Rolling Shutter Mode - Readout

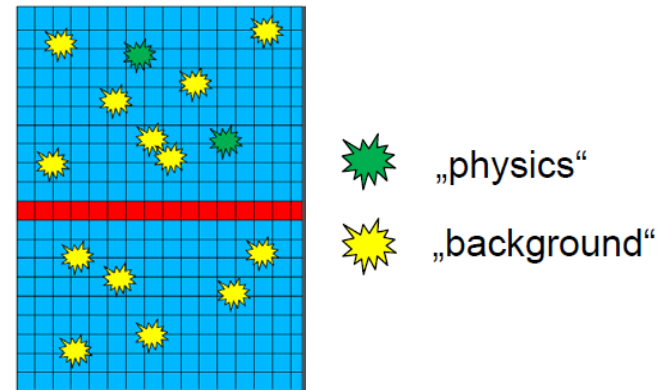
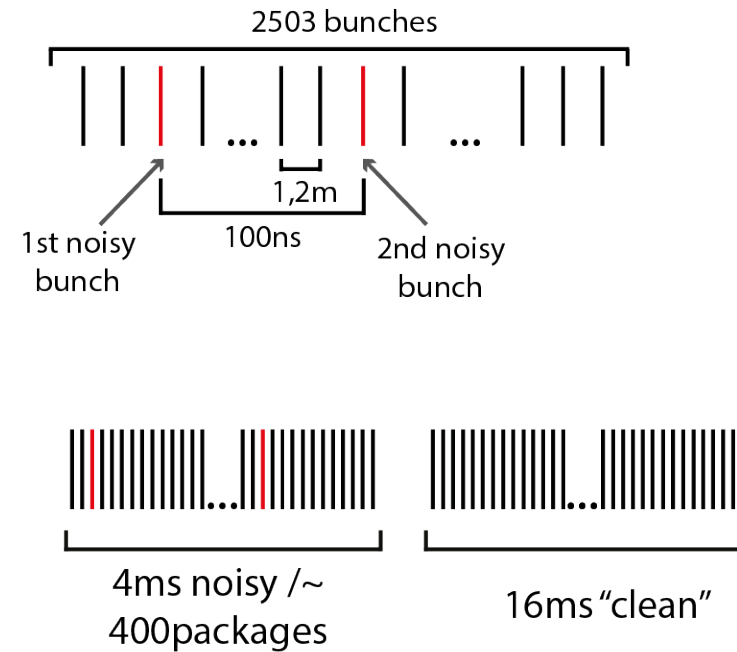
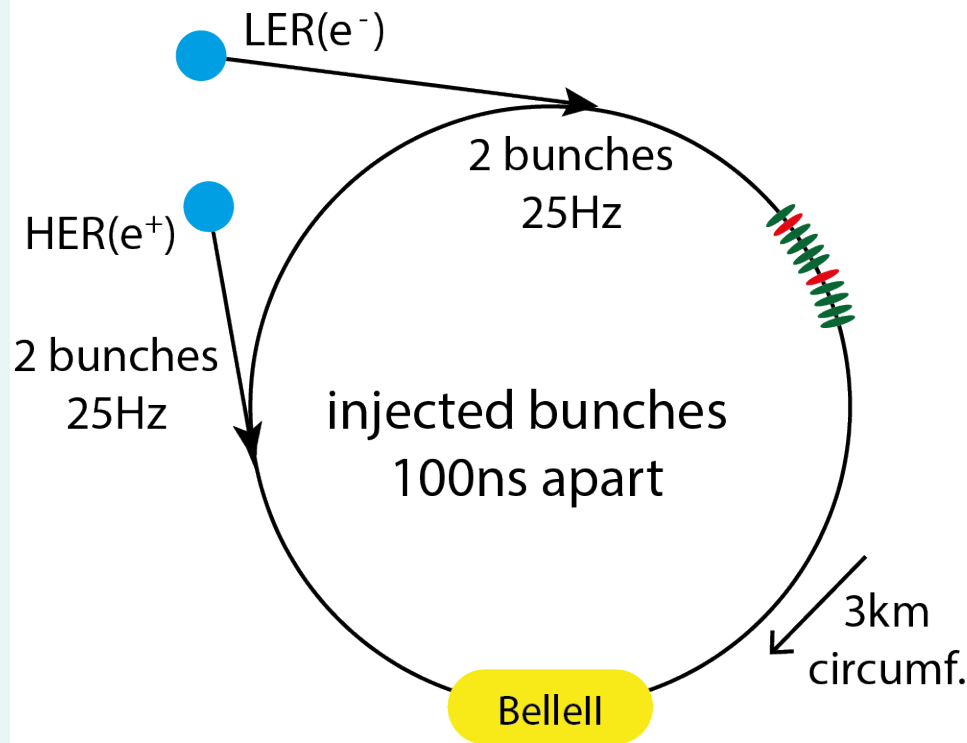
Rolling Shutter Mode

- Low power consumption; only one row is active; all are sensitive
- Single Sampling (pedestal subtraction and common mode correction)
- Readout time: 20 μs for entire frame (50 kHz)
- Read-Clear cycle: 100 ns



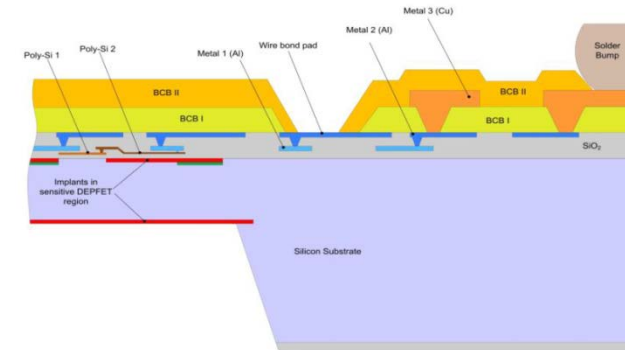
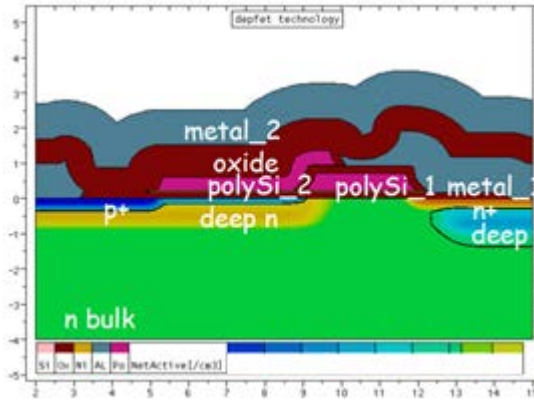
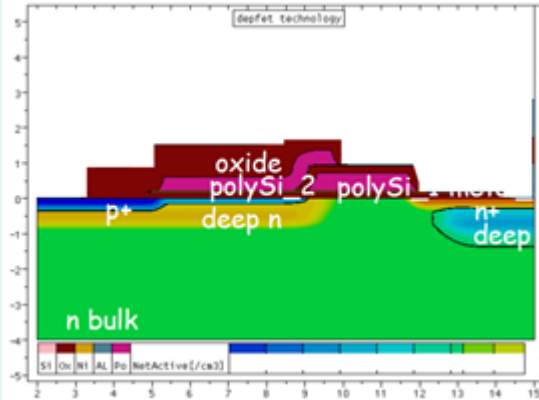
one ADC per column

Gated-Mode Operation



Continuous injection scheme; total rate: 50 Hz
 Due to Liouville theorem injected bunches need to cool (4ms); results in „noisy“ particles
 Very large occupancy („junk charge“)
 If similar damping is assumed for SuperKEKB => 20% downtime for PXD

Processing



Phase I – before metal

- Implantations
- Polysilicon
- Dielectric depositions

front end of line

Phase II – Aluminum

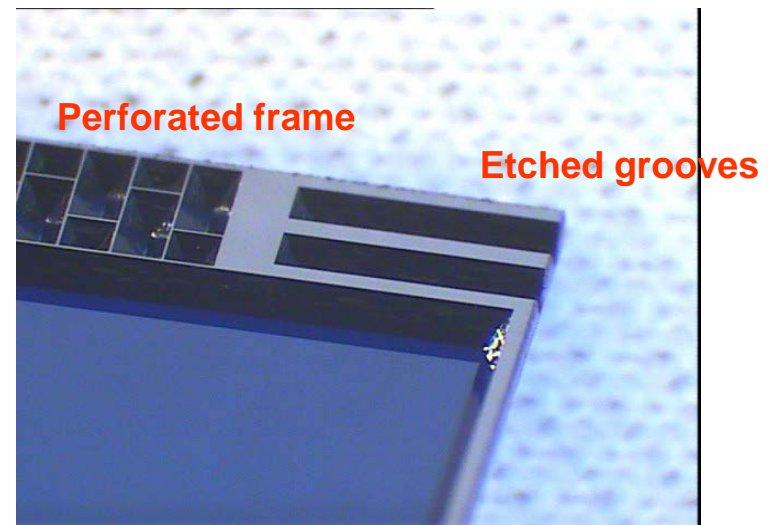
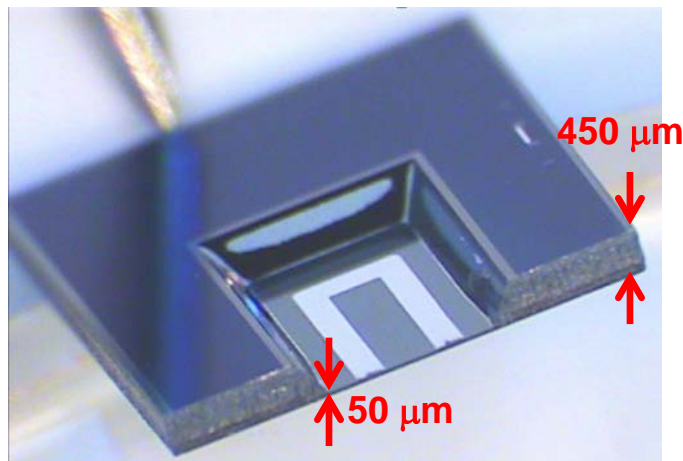
- Metal 1
- Isolation
- Metal 2

back end of line

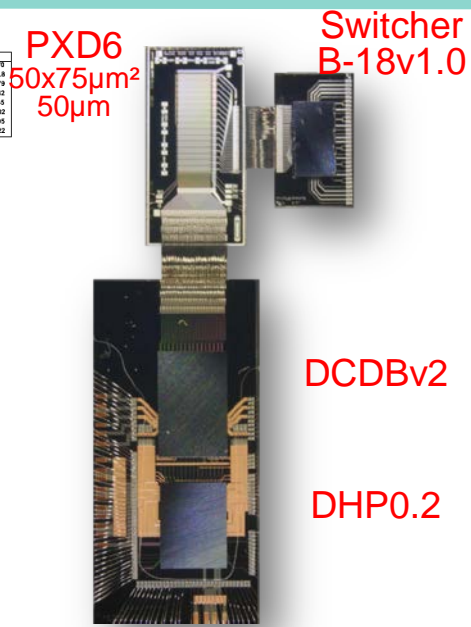
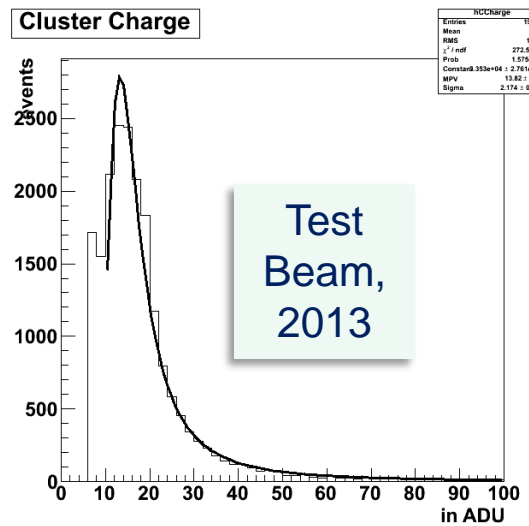
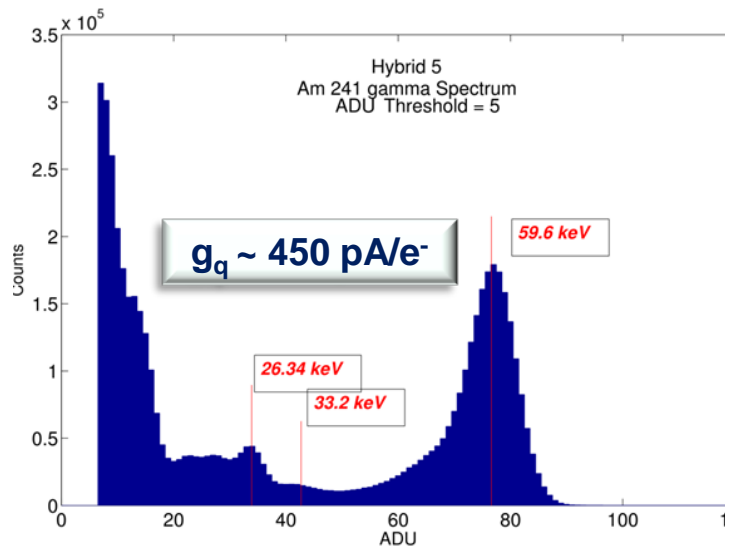
Phase III – Thinning & Copper

- Handle Wafer Removal
- Dielectric deposition
- Metal 3
- Passivation

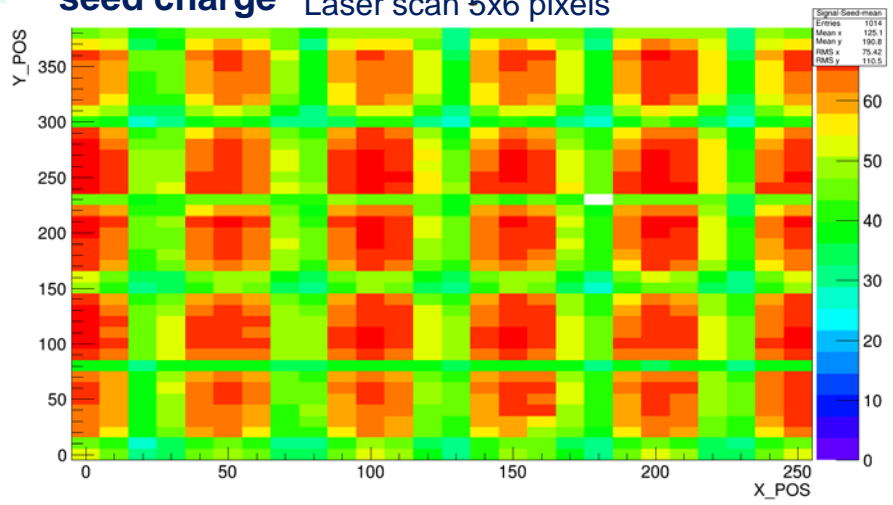
Thinning Technology



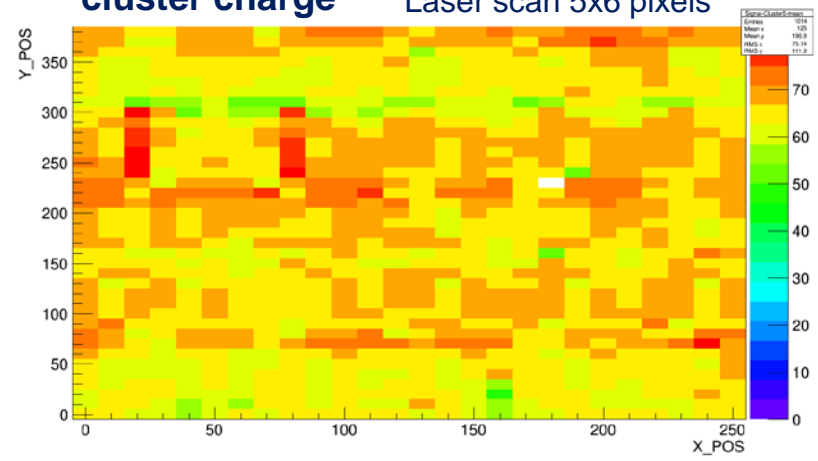
Lab measurements and Beam Test



seed charge Laser scan 5x6 pixels

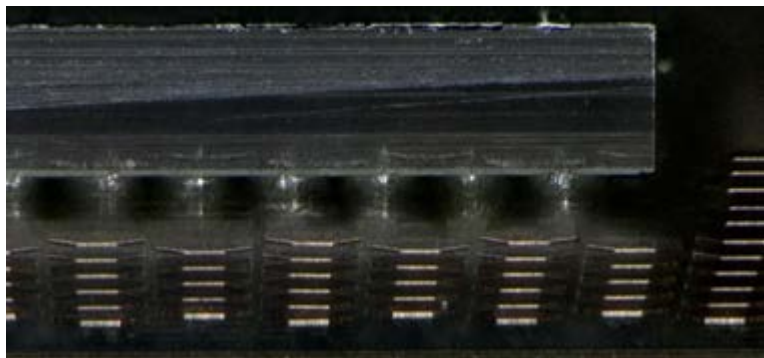


cluster charge Laser scan 5x6 pixels

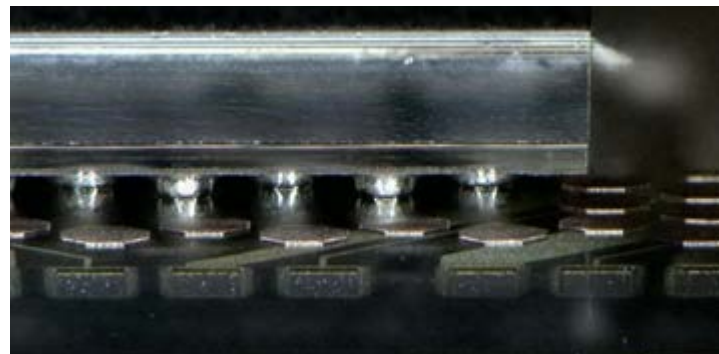


Homogeneous charge collection

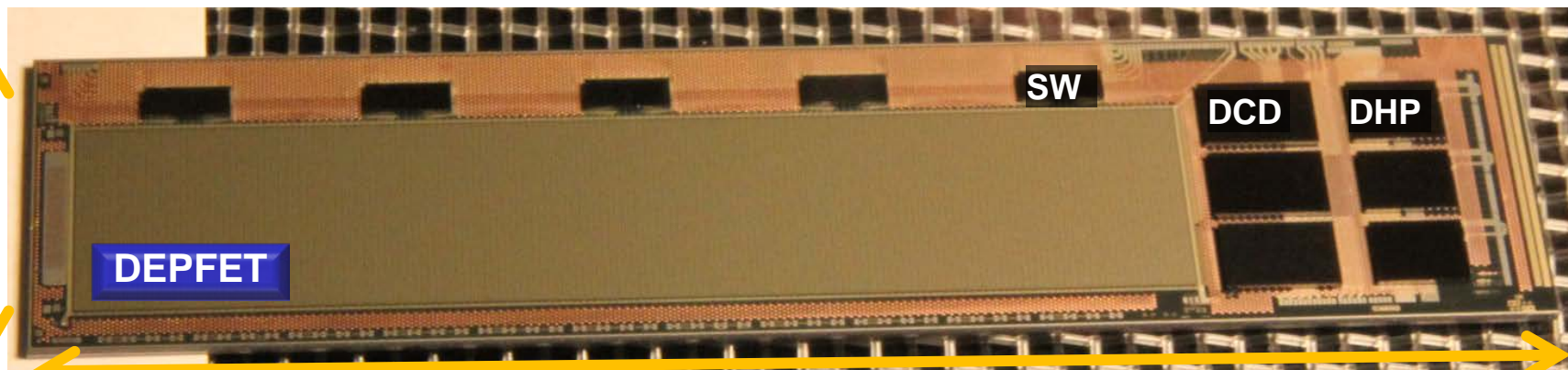
Large PXD6 Prototype Matrix – fully populated module



Switcher-B18v2.0



DCD-Bv2



DEPFET

SW

DCD

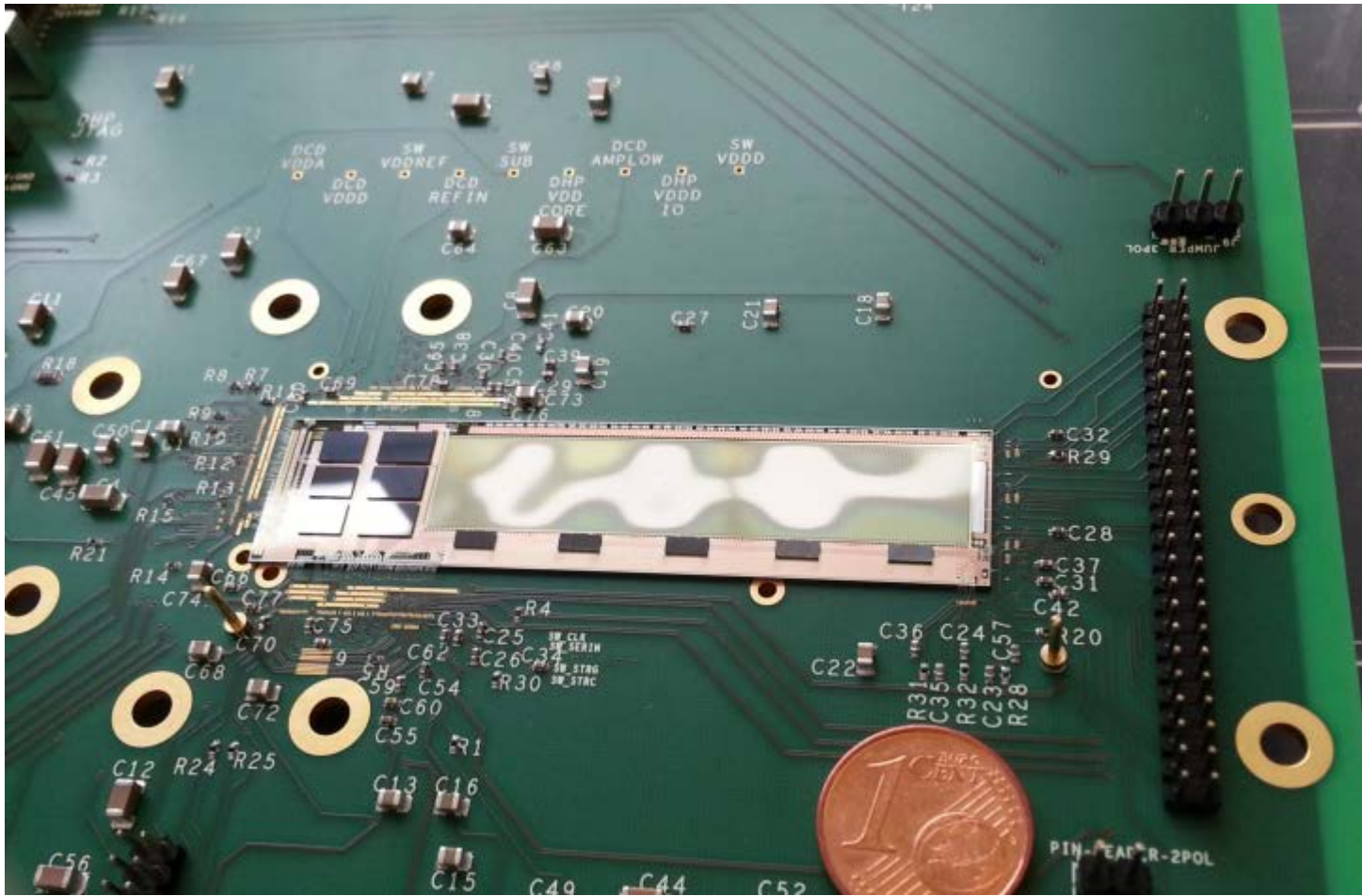
DHP

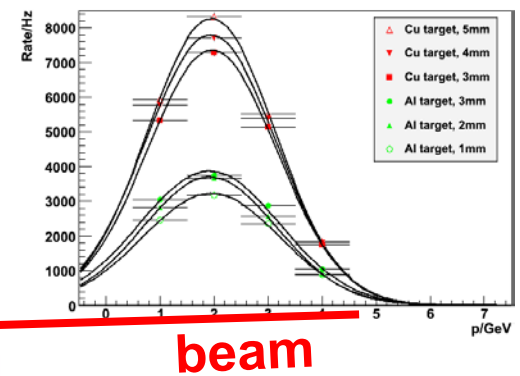
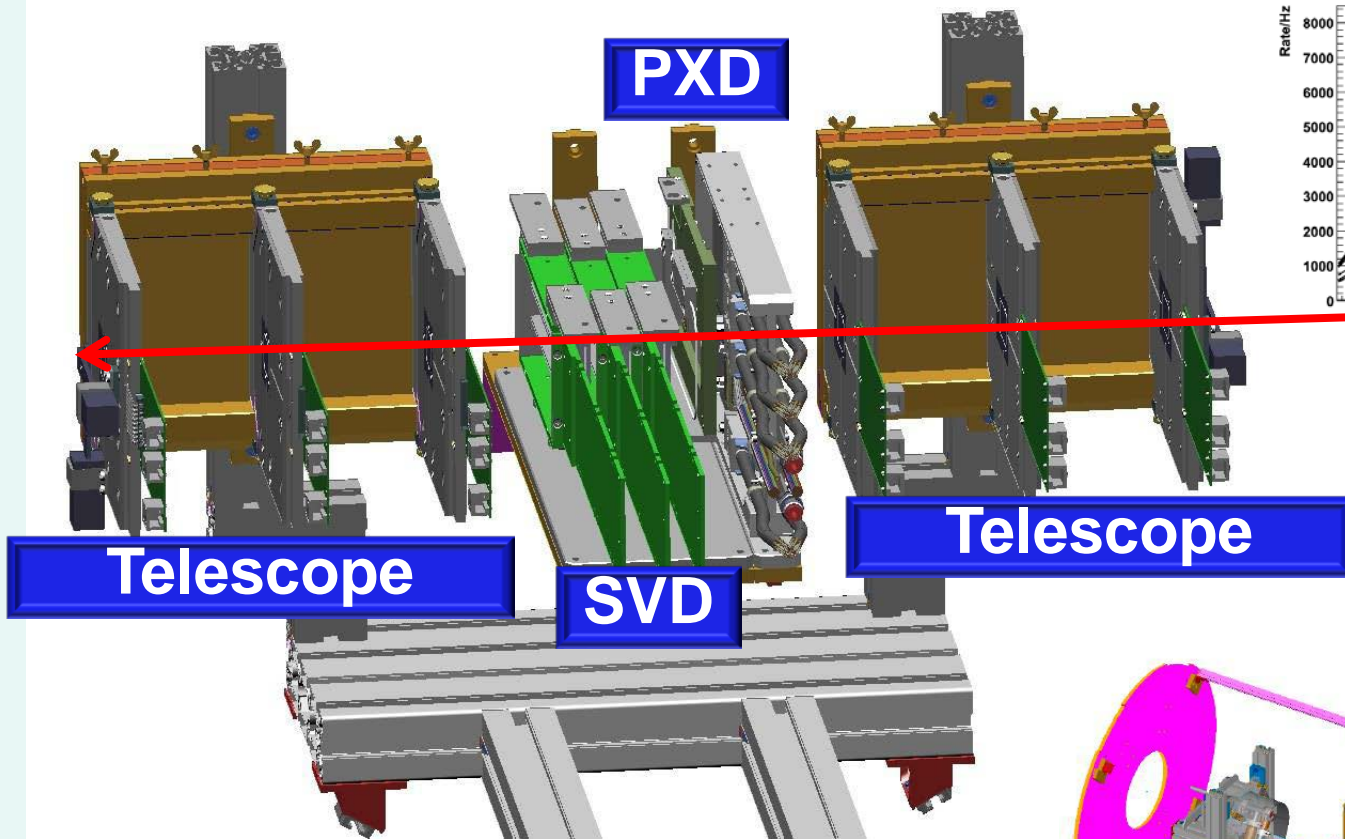
66 mm

Belle II pixel cell design
640x192 pixels matrix
50x75x50 μm^3 pixel cells

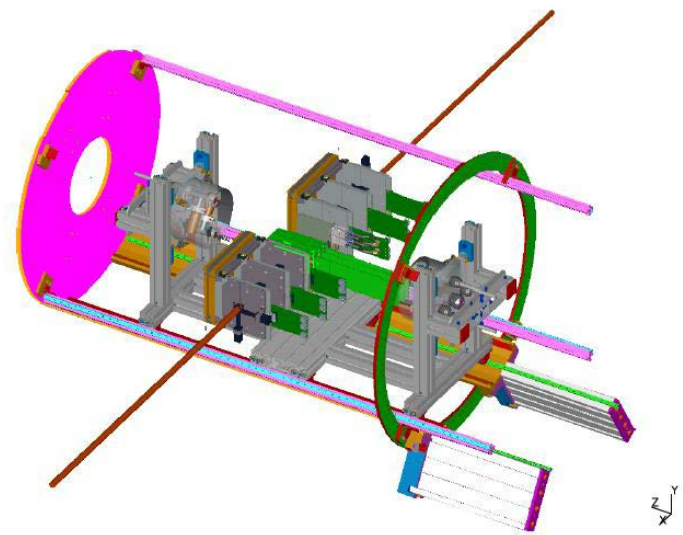
Testbeam 2014 at DESY (Hamburg, GER)

Glue (between PCB and PXD6 module): Epotek 920 EL, cure at 120°C
 Due to different coefficients of thermal expansion
 ⇒ Bowing of matrix (crest & valley: 80 μm at a distance of 1 cm)

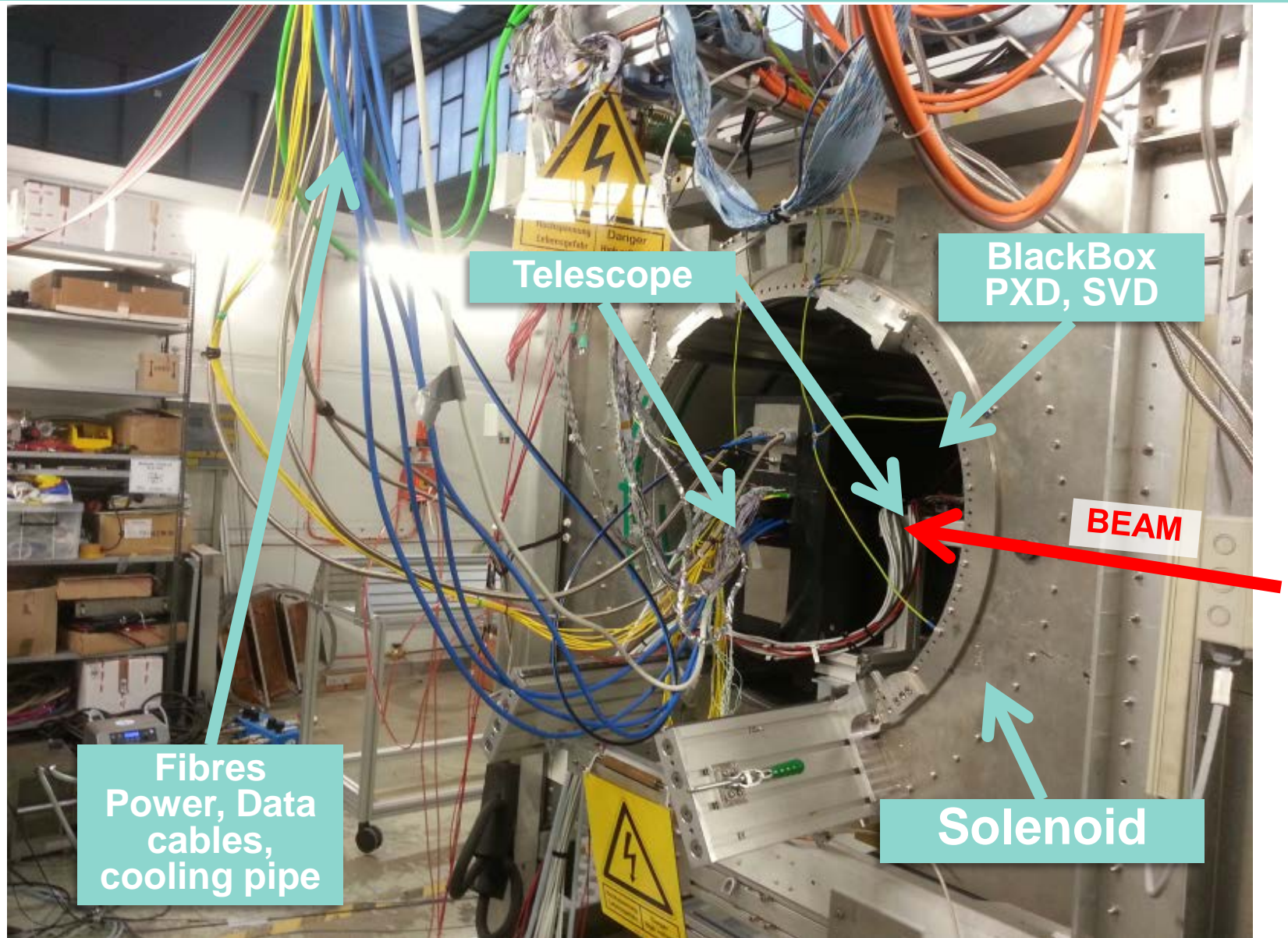




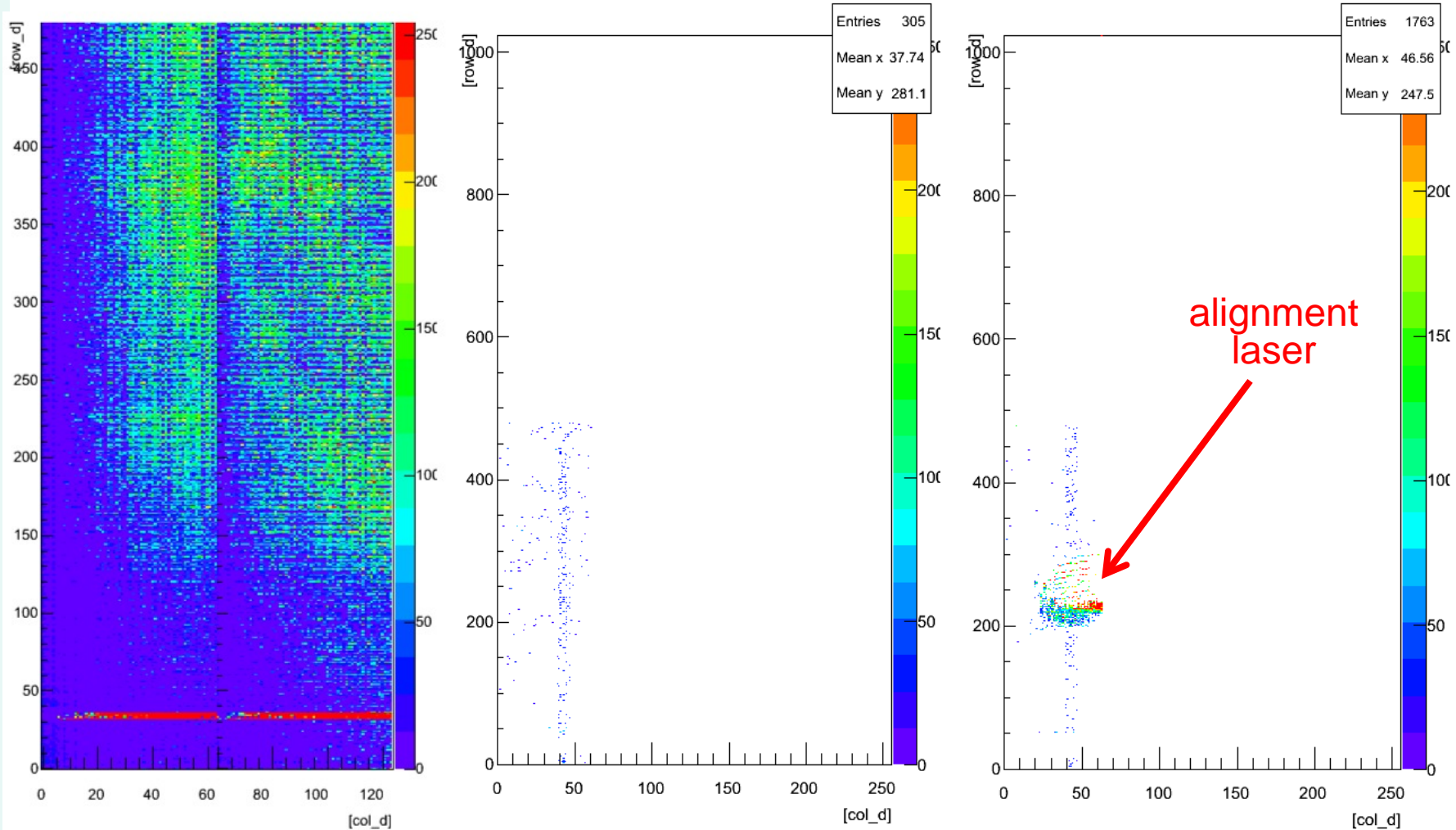
1 Tesla Solenoid Field



Setup – Testteam 2014 – DESY



Results – Testbeam 2014 - DESY

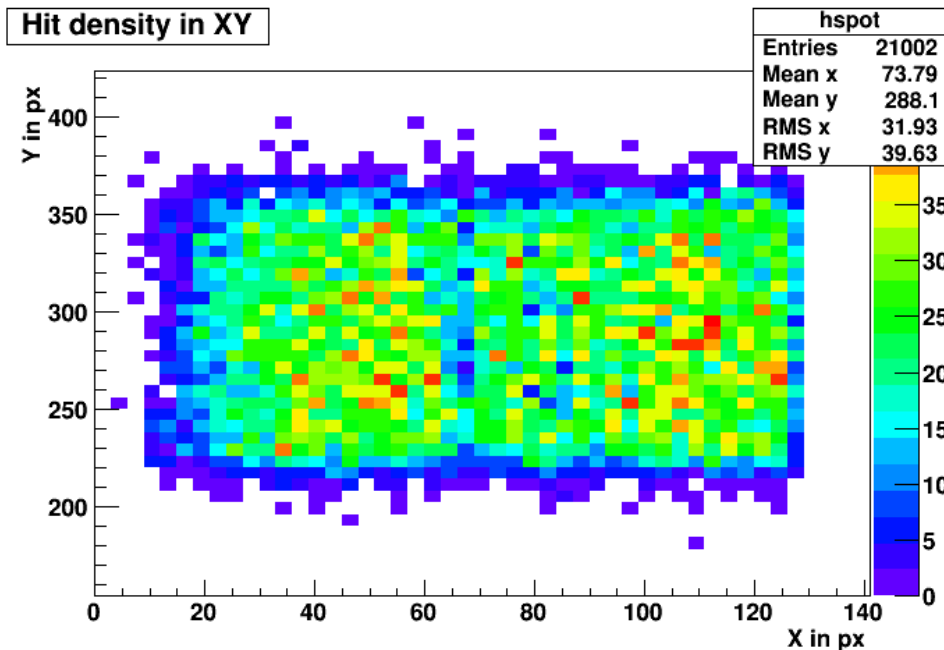


Pedestal distribution
(dominated by induced stress)
non irradiated devices

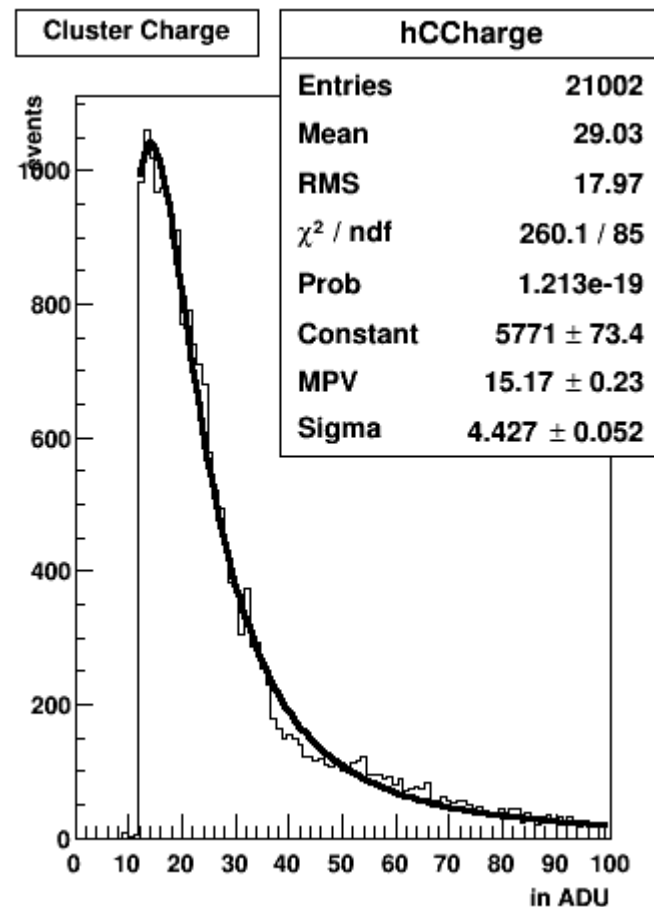
Zero suppressed
frame

Zero suppressed
frame – laser spot

Results – Testbeam 2014 - DESY



DEPFET PXD6 HitMap
Beam Spot: 11 x 6 mm²



Cluster Signal
MPV ~ 15ADU

DEPFET Collaboration

- CNM/IFAE, Barcelona
- Charles University, Prague
- DESY, Hamburg
- HLL, Munich
- IFCA, Santander
- IFIC, Valencia
- IFJ PAN, Krakow
- IHEP, Beijing
- KEK-PF, Tsukuba
- KIT, Karlsruhe
- LMU Munich
- MPI for Physics, Munich
- TU, Munich
- University of Barcelona
- University of Bonn
- University of Heidelberg
- University of Giessen
- University of Göttingen



Summary

- To fully exploit the high luminosity (increase by factor 40), the detector is currently upgraded
- Excellent *spatial resolution* of $\sim 15 \mu\text{m}$; *occupancy* $\sim 1\%$, fast readout (50 kHz frame rate), huge number of pixels ($\sim 8 \text{ Mpix}$) \Rightarrow fits all the requirements for Belle II
- Complex DEPFET *technology*, fully functional; successful demonstration in lab and beam tests
- Thinning of sensitive area down to $50\mu\text{m} / 75 \mu\text{m}$ ($0.2\% X_0$), minimizing multiple scattering;
- Low *power consumption* $\sim 18 \text{ W}$ per ladder
- ASICs and Sensors close to final version
- Signal to Noise: ~ 40 (including noise from ASICs)
- Many aspects not covered in this talk; though in development by the Collaboration

Backup

Radiation Tolerance

Gate Dielectrics: ~ 200nm

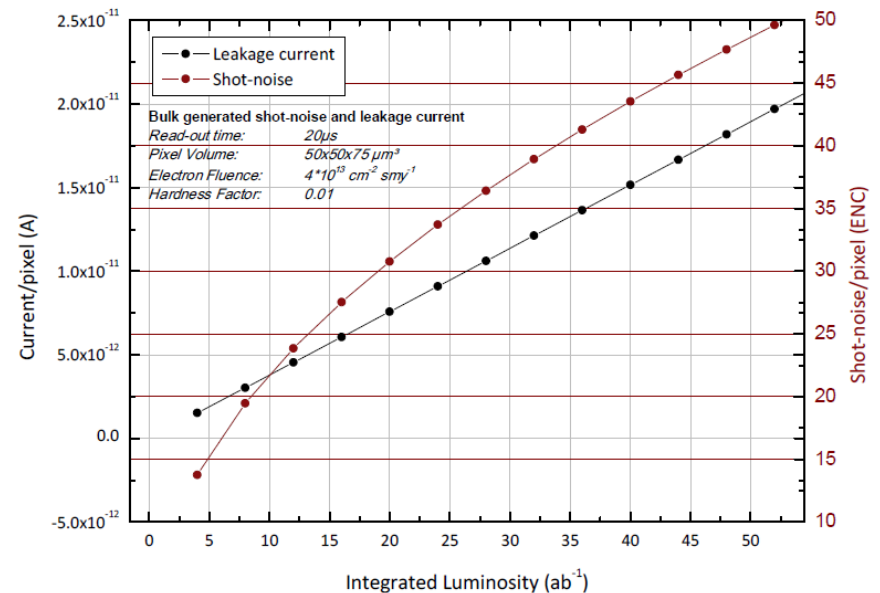
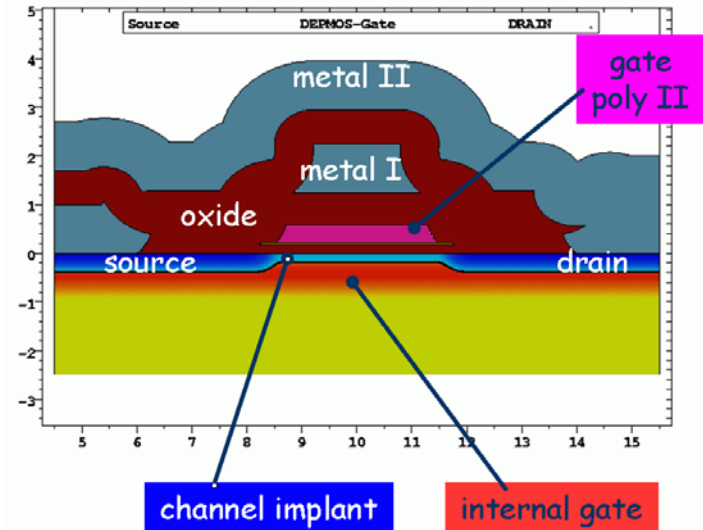
- ▷ Radiation field at Belle II dominated by ~MeV electrons/positrons from QED beam background

Ionizing Radiation - Total Ionizing Dose (TID)
(~2Mrad/a at Belle II)

- Positive fixed oxide positive charge $\rightarrow \Delta V_T$
- interface trap density \rightarrow
 - reduced mobility (g_m)
 - higher 1/f noise

Non Ionizing Energy Loss (NIEL)
($10^{12} n_{eq}/cm^2/year$ at Belle II)

- leakage current increase \rightarrow shot noise
- trapping not considered to be critical
- Type inversion expected after $10^{14} n_{eq}/cm^2$



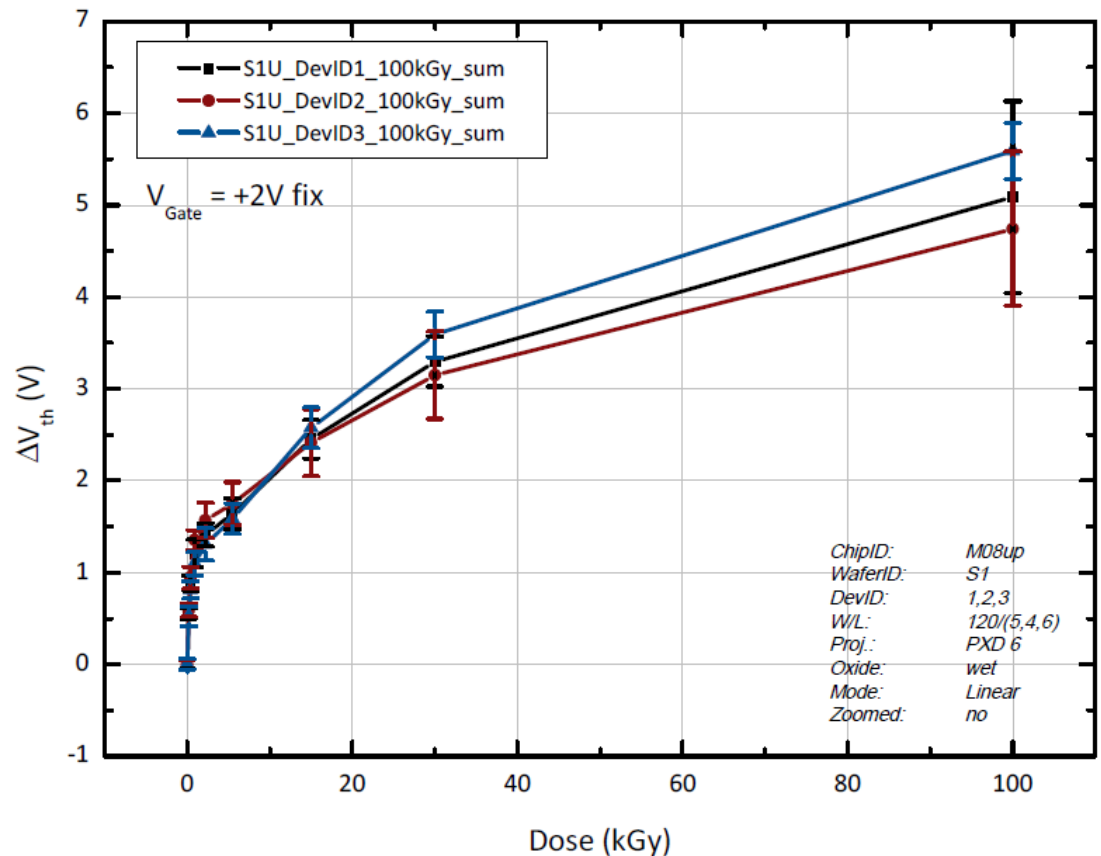
Radiation Tolerance

R&D since 2008:

- ▷ Reduce t_{ox}
- ▷ Optimize gate dielectric layer

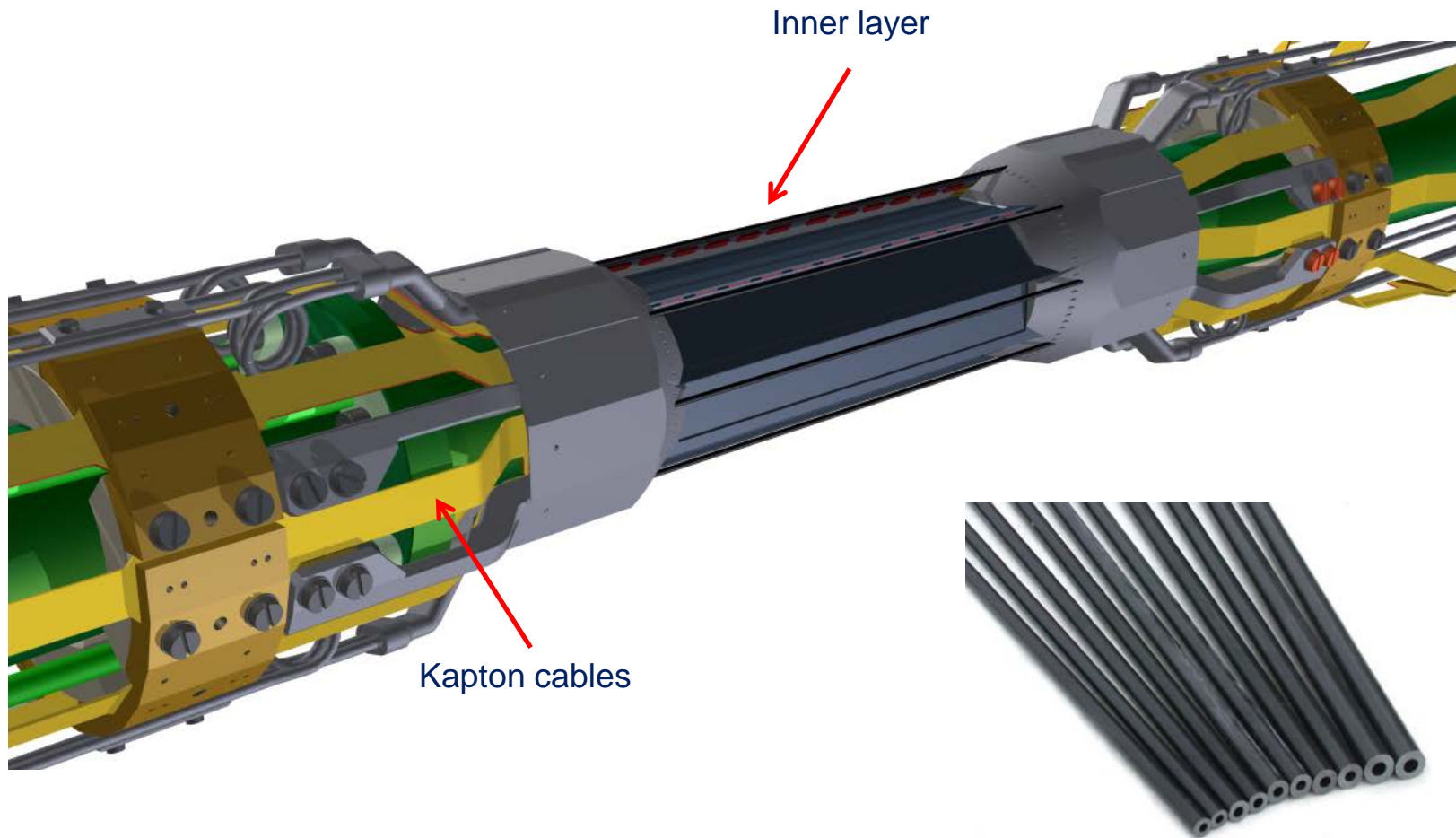
$\Delta V_{th}(10\text{Mrad})$: $\sim 15\text{V} \rightarrow 3\text{V}$

The remaining small threshold voltage shift can easily be compensated by a shift of the operating voltages of the DEPFET!



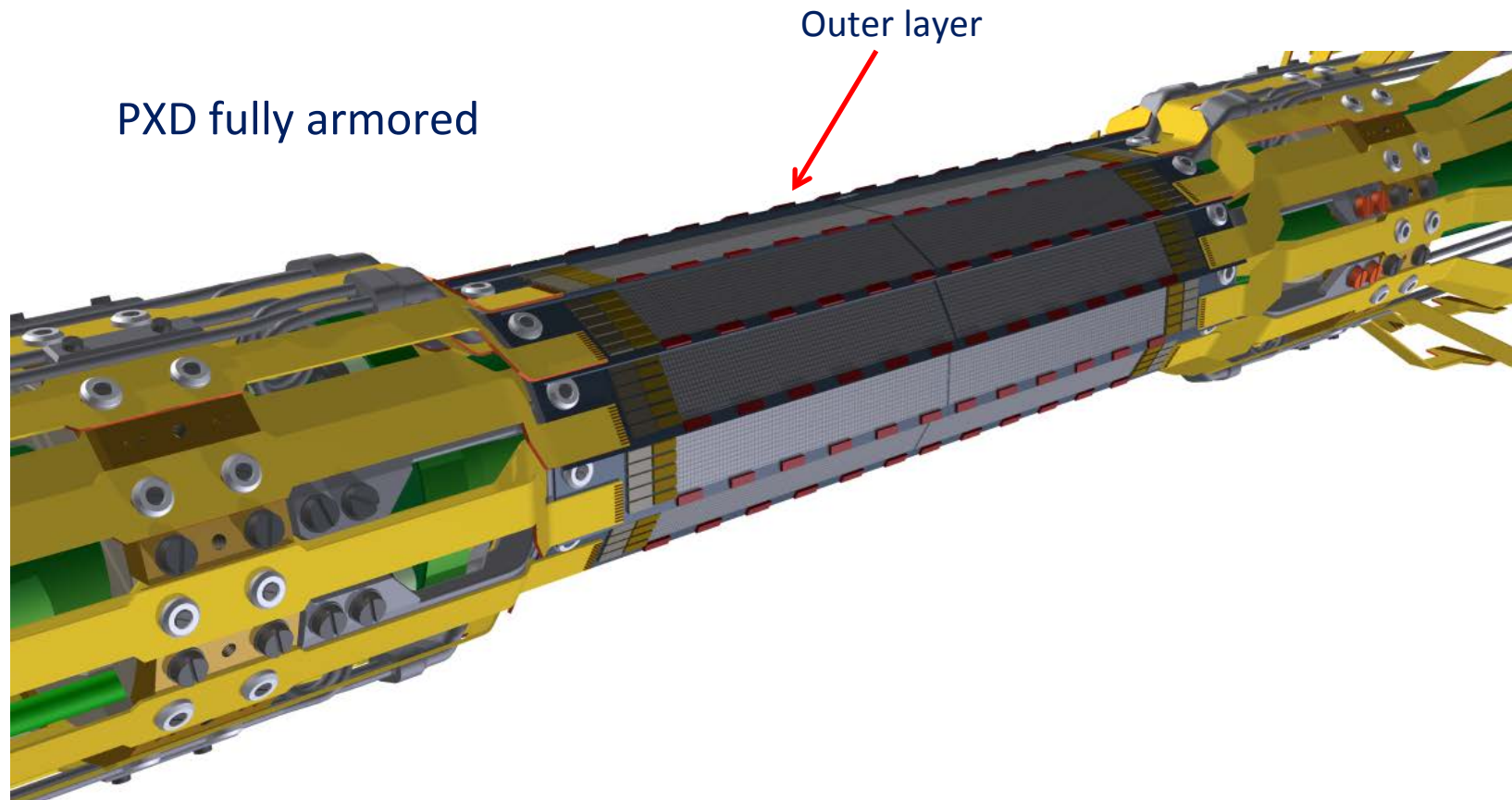
→ Safe operation for about 10 years in Belle II

Belle II – Pixel Detector – Inner Layer



Inner layer close to the IP (14mm)

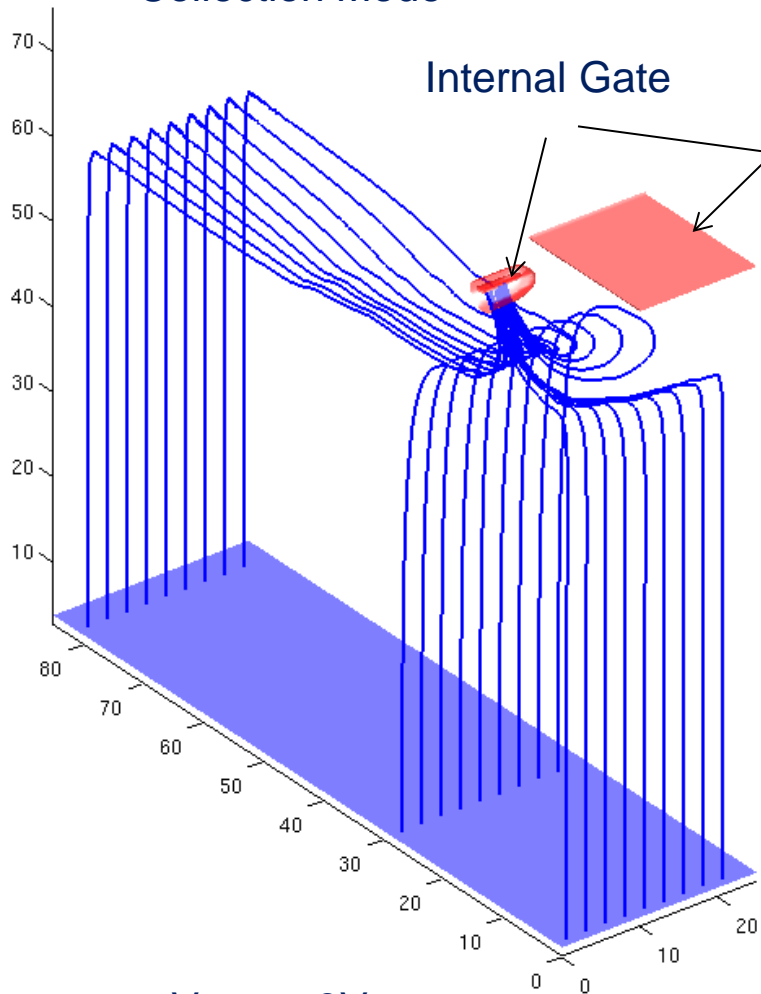
Additional carbon fibers capillaries to cool the Switchers, if needed (not tested yet)



- Low material budget cooling
- Massive structures outside the acceptance to cool down the readout chips
- The center of the ladder rely on cold air

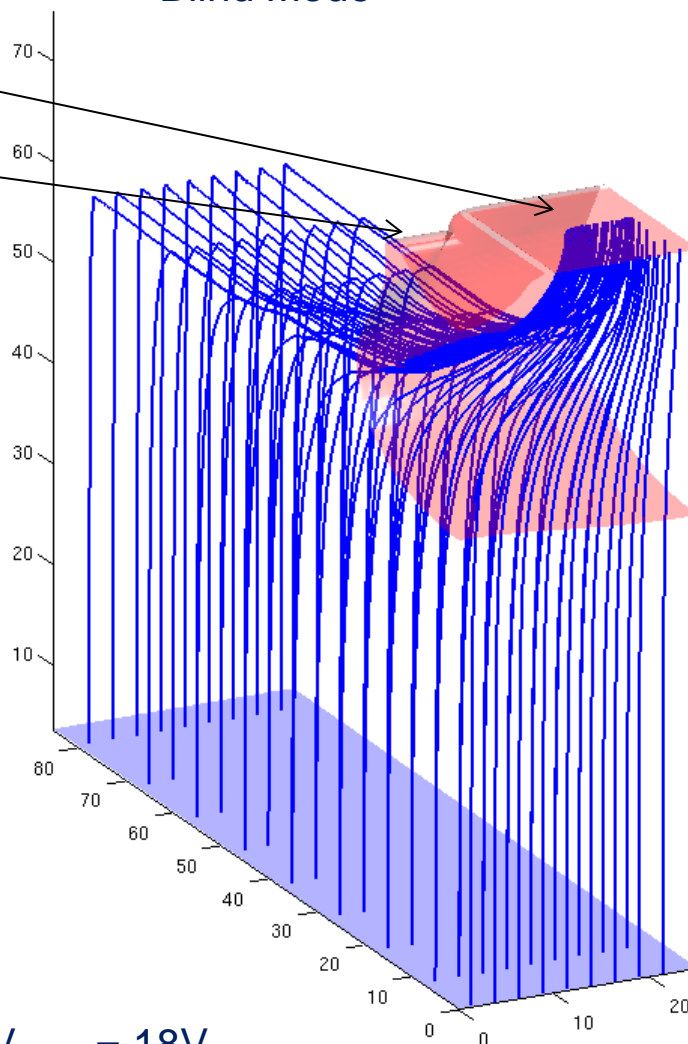
Gated Mode – Simulations – trajectories of electrons

Collection Mode



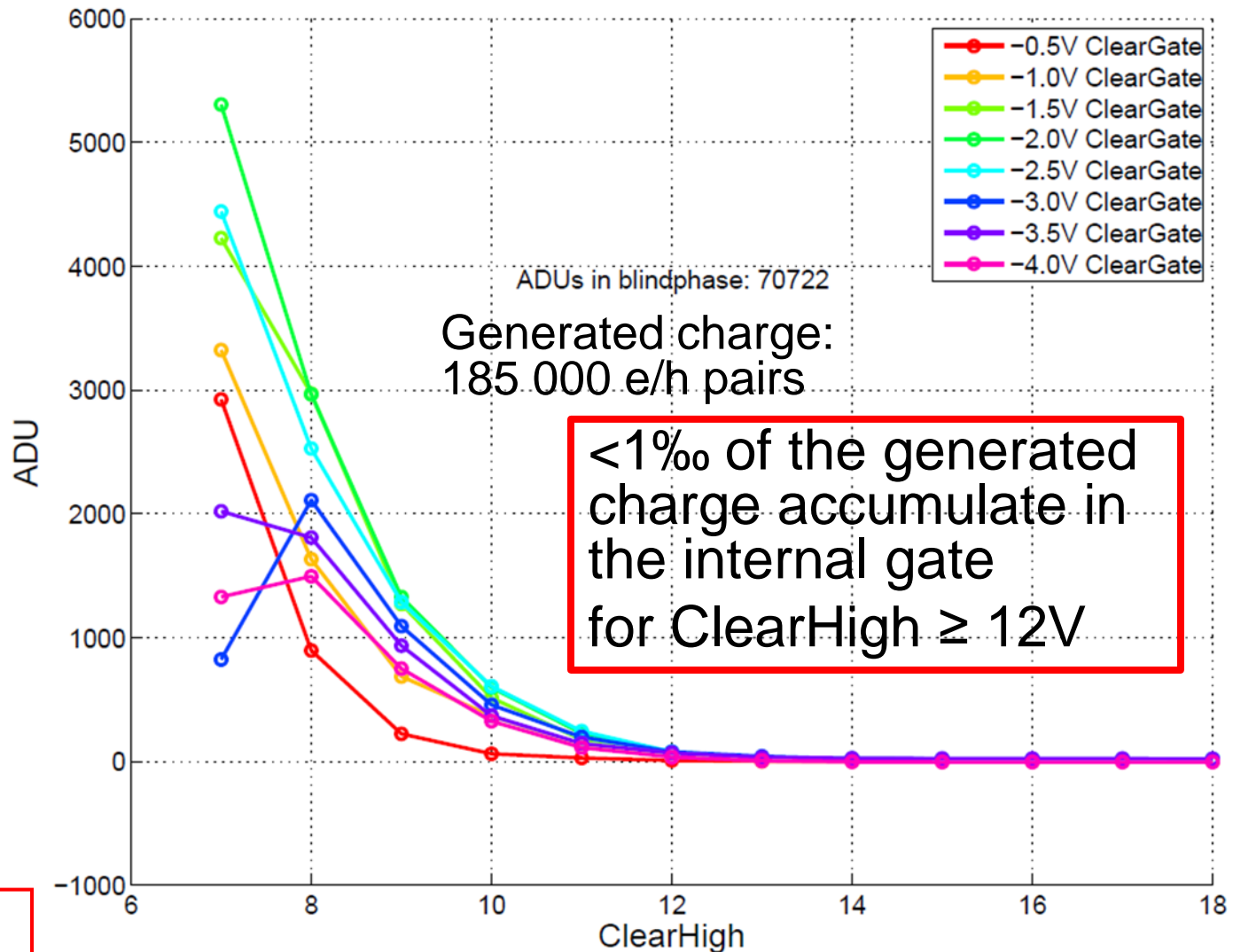
$$V_{\text{Clear}} = 3\text{V}$$

Blind Mode

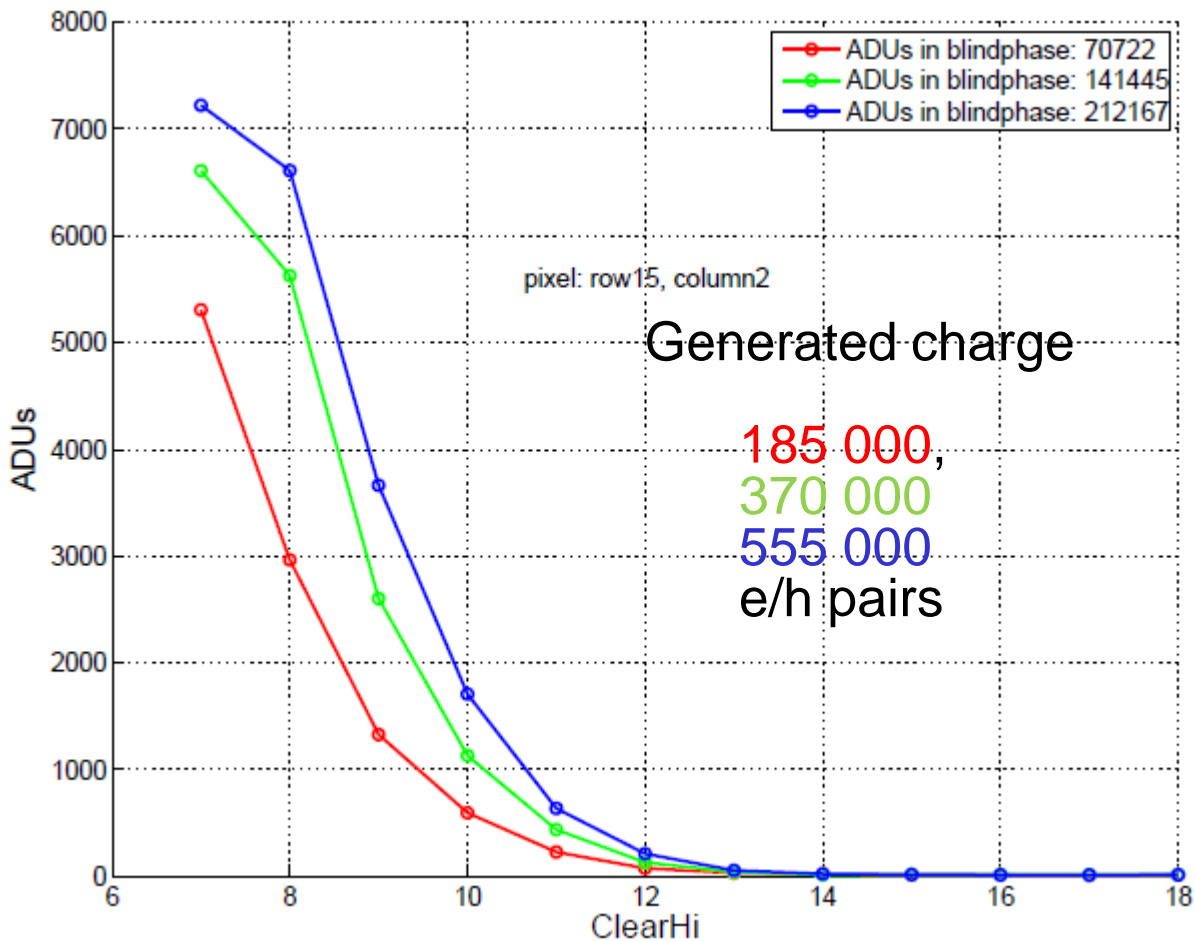


$$V_{\text{Clear}} = 18\text{V}$$

GM: Generation of Junk Charge – CCG dependance

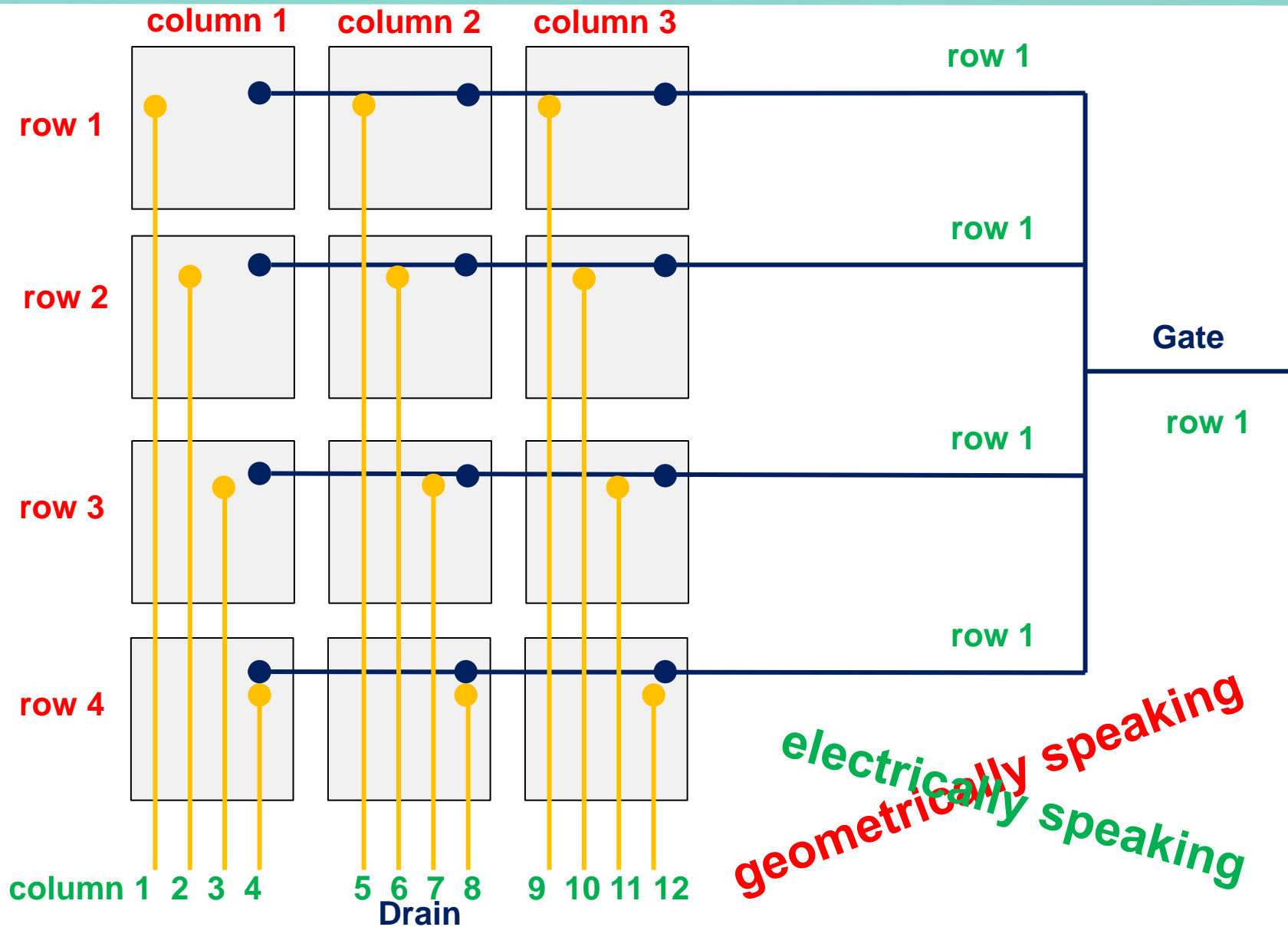


1ADU = 2.61 electrons



**1ADU
=
2.61 electrons**

Four Fold Readout



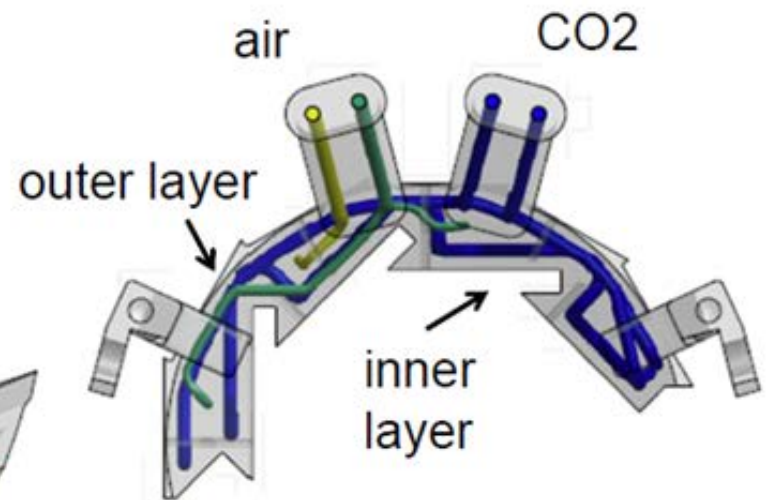
Cooling Issues

Beampipe support

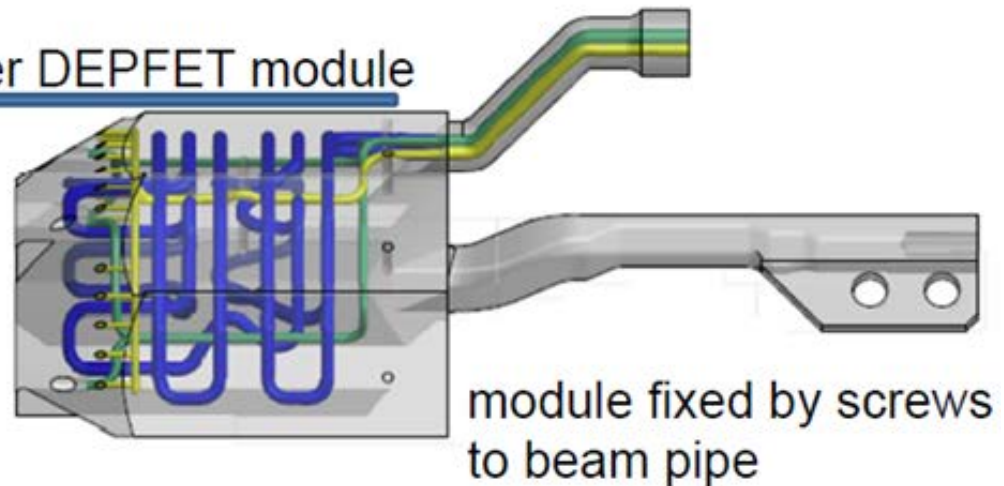
CO2 channel (in/out)

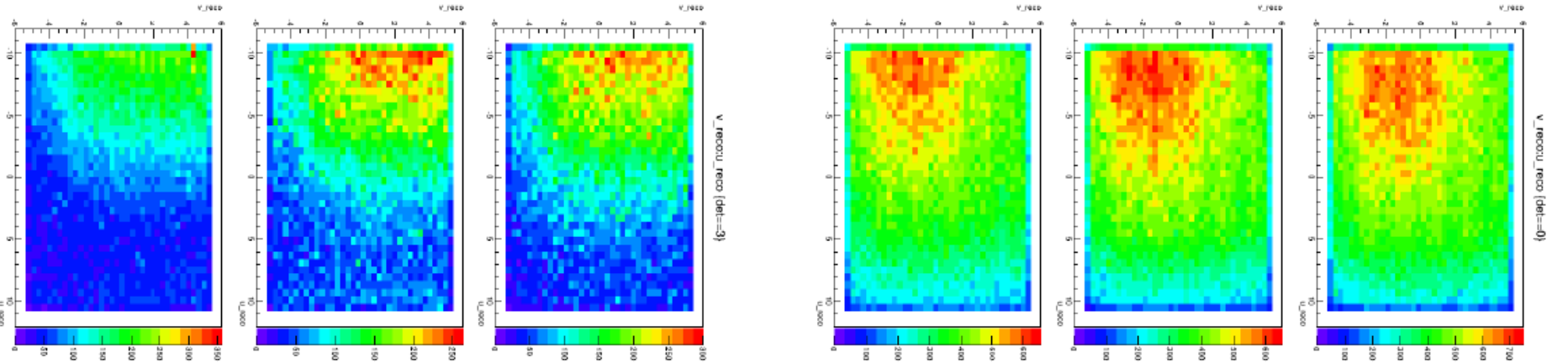
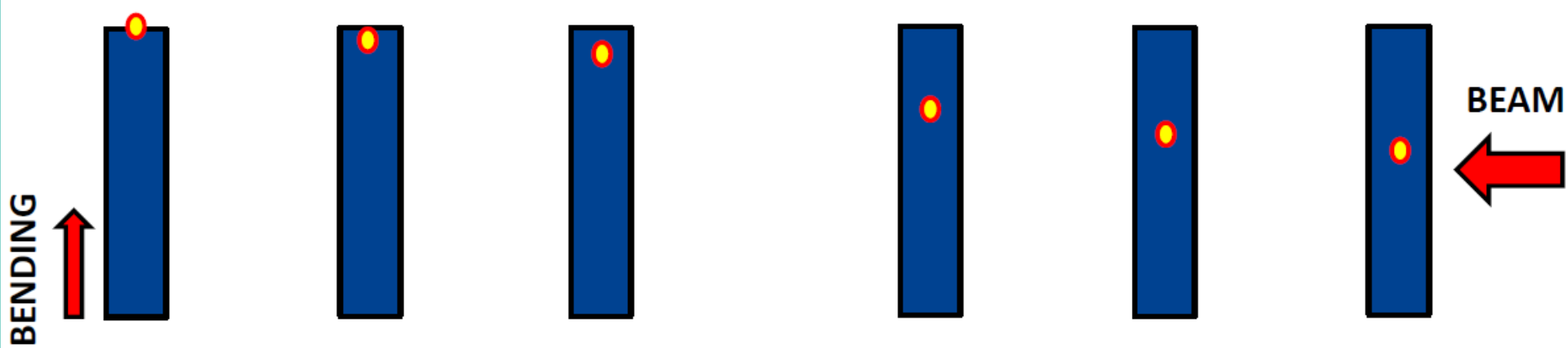
air channels (in only)

design: MPI
manufactured by Fruth Innovative Technology (FIT)



outer DEPFET module





Beam: 5GeV, 1T Magnetic Field



Abbreviations

DCD = Drain Current Digitizer

DHP = Data Handling Processor

DEPFET = DEPIeted p-channel Field Effect Transistor

IP = Interaction Point

MIP = Minimum Ionizing Particle

MPV = Most probable value

PXD = Pixel Detector

S/N = Signal to Noise Ratio

SVD = Silicon Vertex Detector (historically based, meaning: silicon strip detector)

X0 = Radiation length = electron loses all but 1/e of its energy

VXD = Vertex Detector